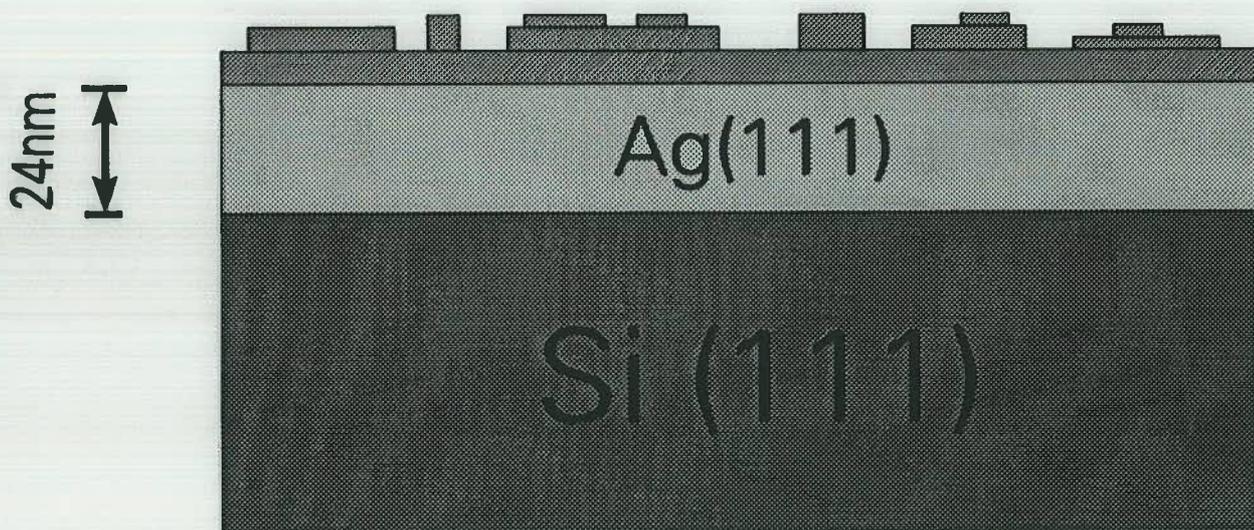


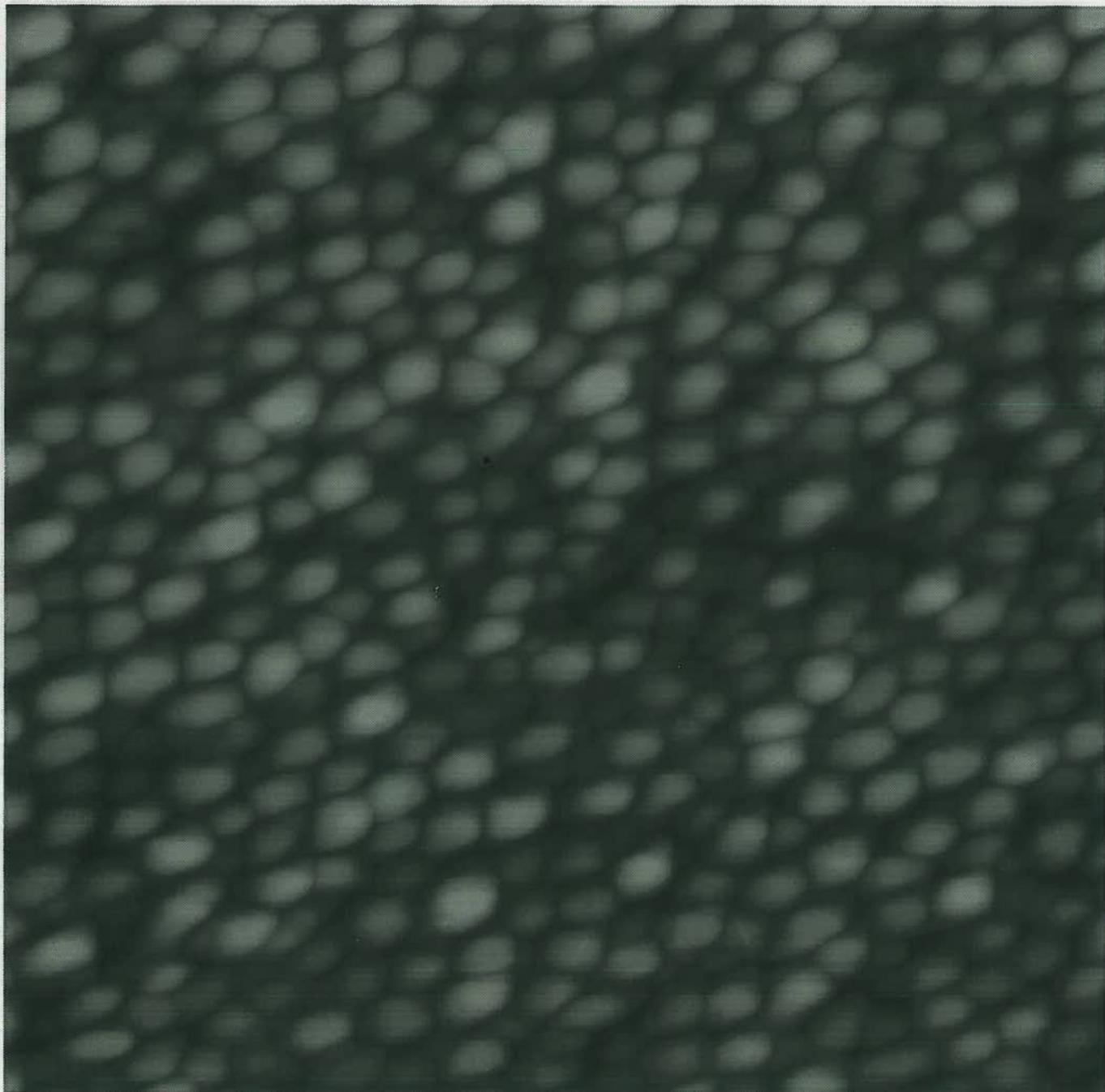
DC-conductivity and SPA-LEED
measurements of the growth
of Ag/Ag(111)/Si(111)



S. Heun, M. Kennedy
E. Luo, M. Henzler

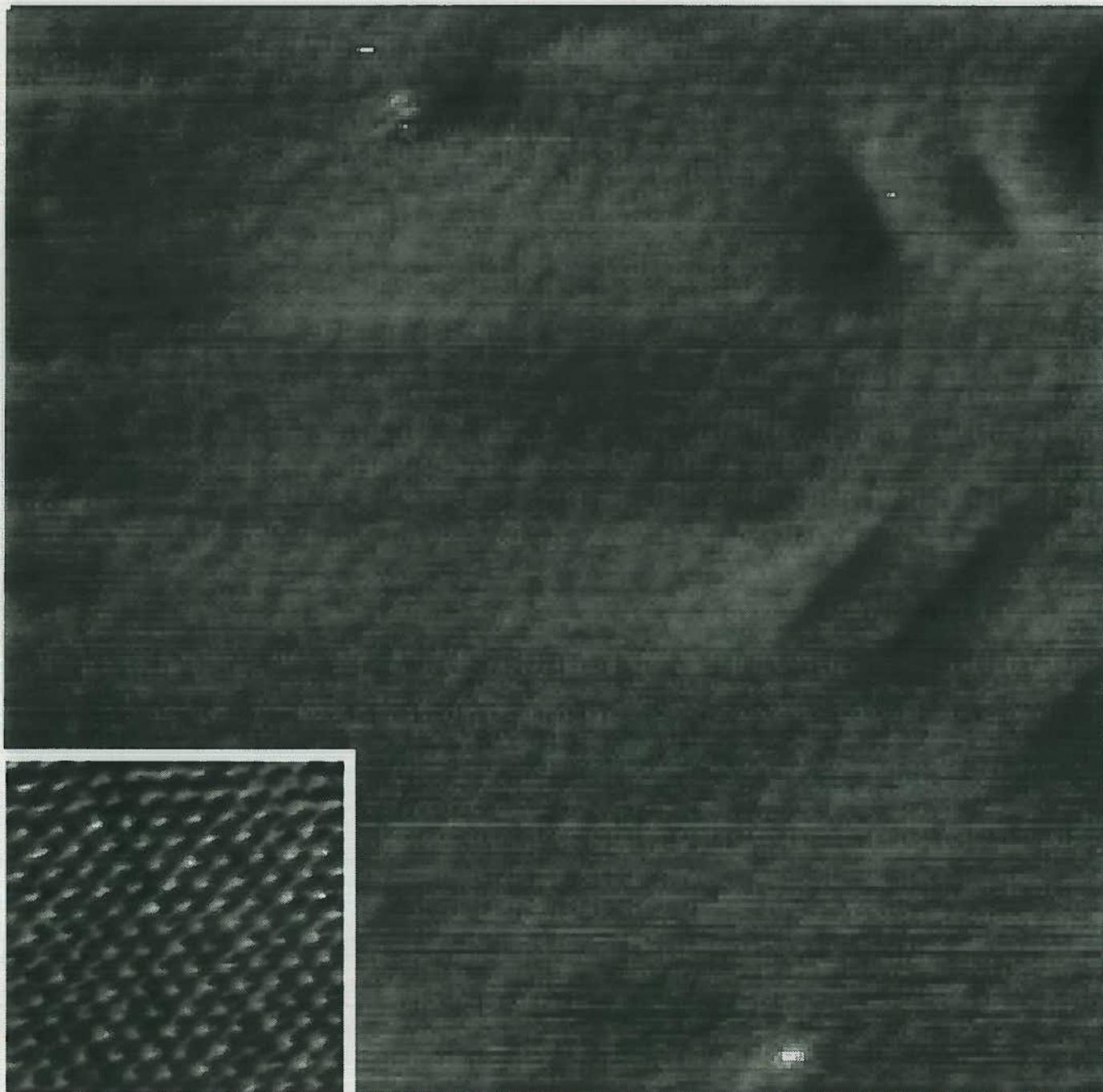
Inst. f. Festkörperphysik
Uni Hannover

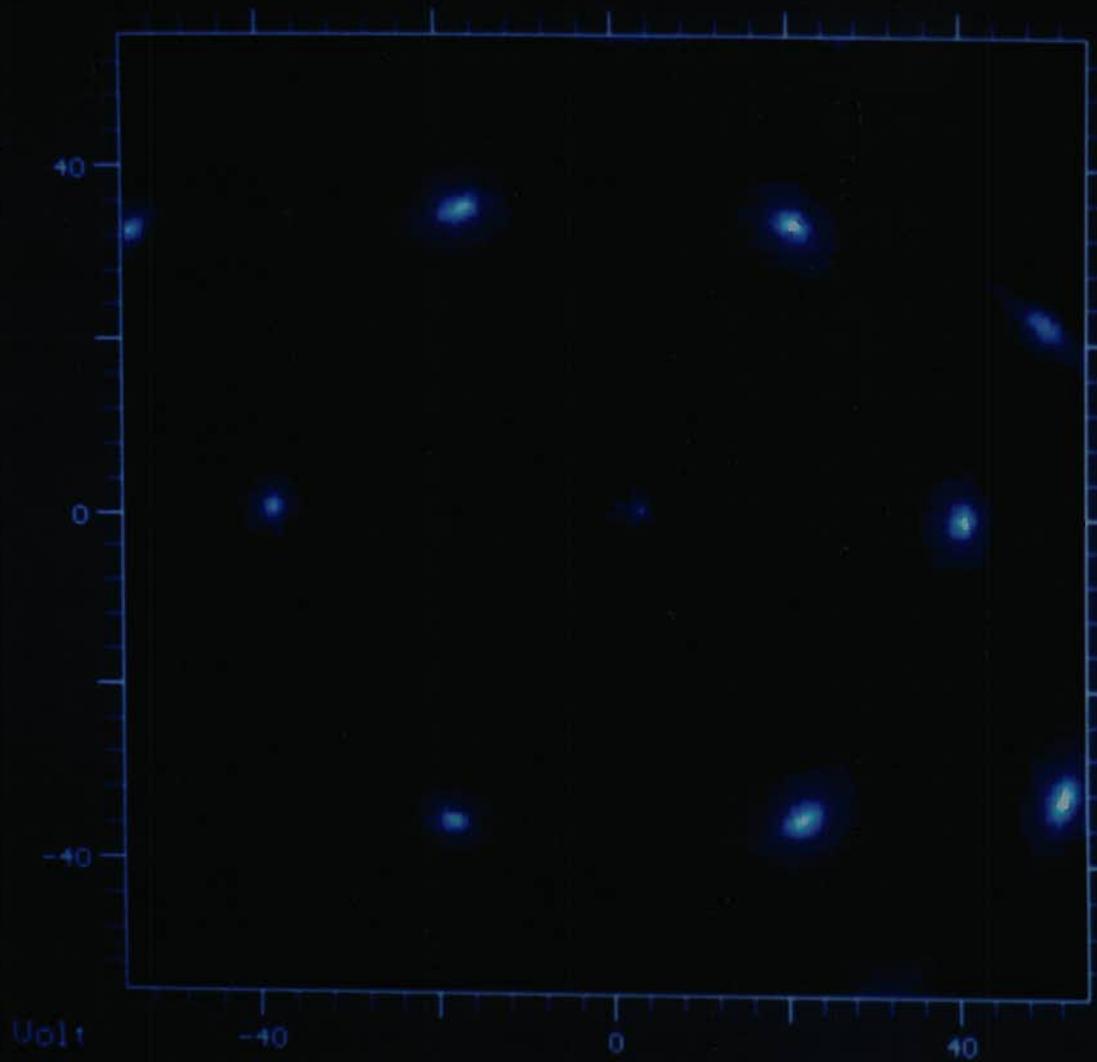
20 ML Ag / Si(111)-7x7 at 80K
920Å x 920Å



© G. Meyer

20 ML Ag / Si(111)-7x7 at 80K,
annealed to 300K
460Å x 460Å





```

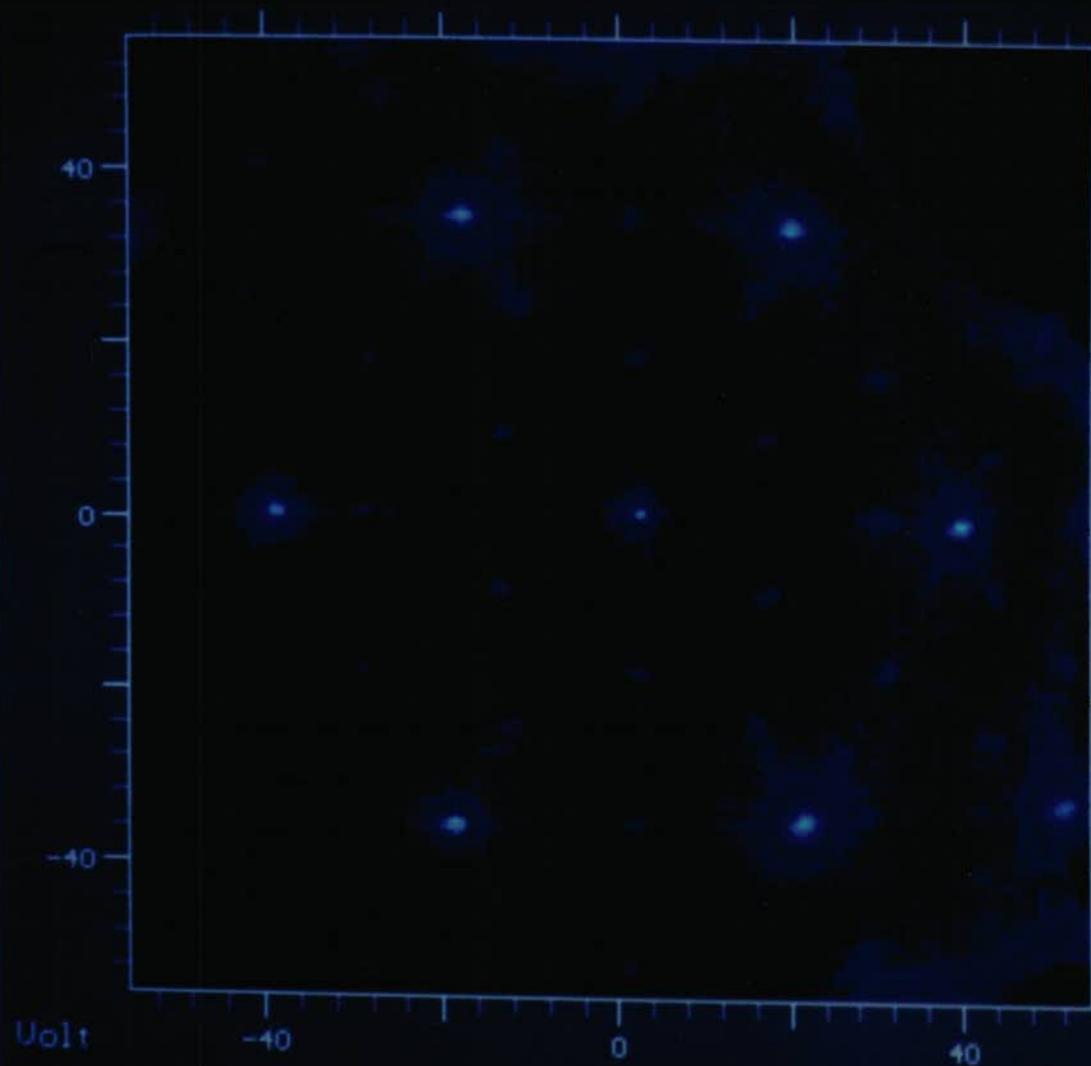
dcl      6.4.1983
Xo      0.00  > 200
Yo      0.00  > 272
Length  110.00 > 371
Alpha   -18.63 > 506

Points   200  > 689
Batetime 110.00 > 939
CpsHigh  6000.0
CpsLow   200.0

Energy   83.0  > 1742
Current  -130.960 > 2373

TotalTime 1:13 h > 3233
100ML Ag/Si(111) > 4404
)300K/400K/130K > 6000
  
```

ContScan	View3d	Contour			Drive a:		Mouse
Opti	Mode	Options	Colors	log	HardCopy	Volt	16:42:33
Scan	Scale	Cursor	Rescale	Store a:	Load a:	SControl	10-Scan



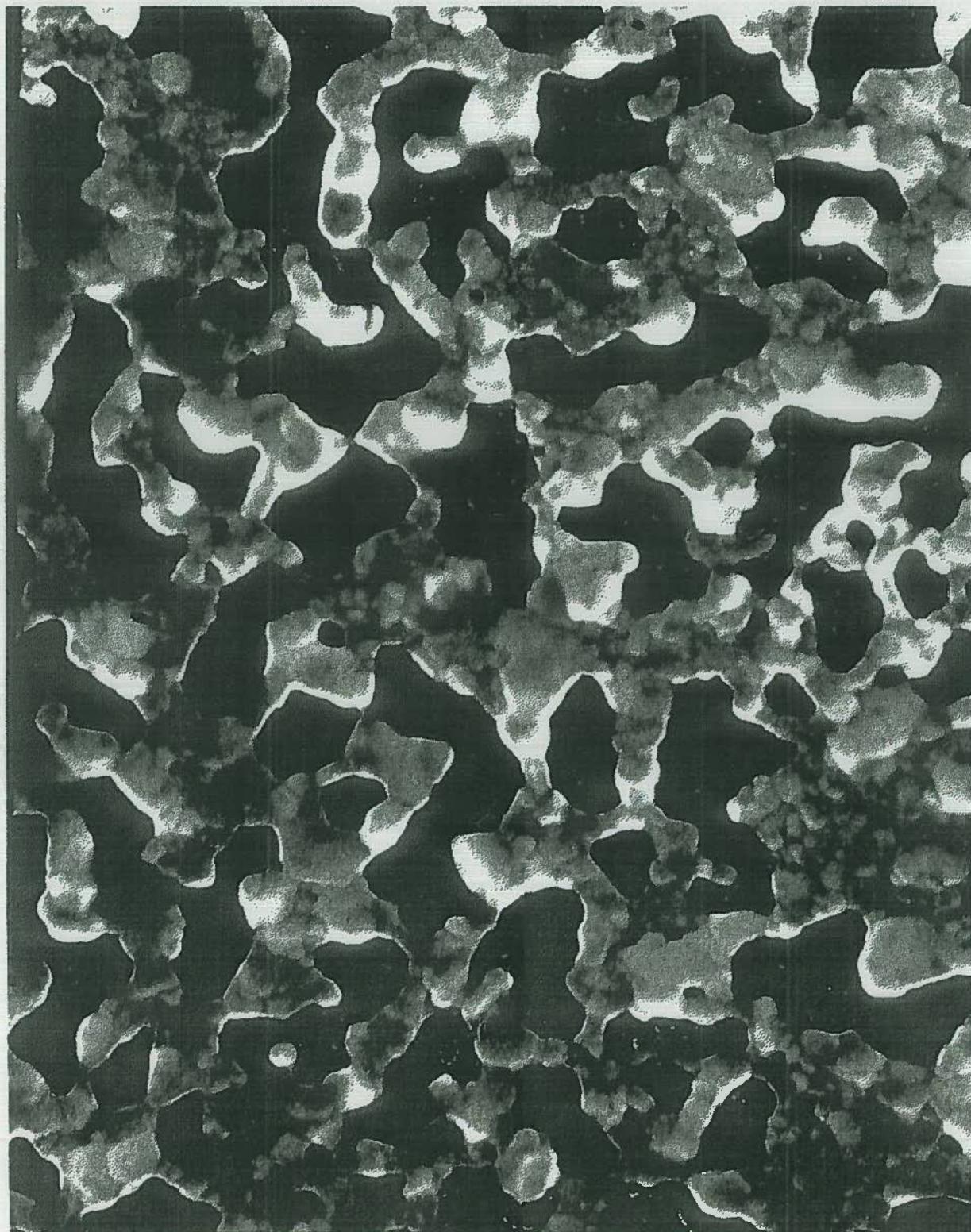
cal 6.4.1993

Xo	0.00	>	175
Yo	0.00	>	293
Length	110.00	>	489
Alpha	-19.61	>	818
Points	200	>	1368
GateTime	80.00	>	2288
CpsHigh	50000.0	>	6396
CpsLow	175.0	>	10695
Energy	83.5	>	17883
Current	-142.510	>	29902
TotalTime	0:53 h	>	50000
100ML Ag/Si(111)			
>700K/130K			

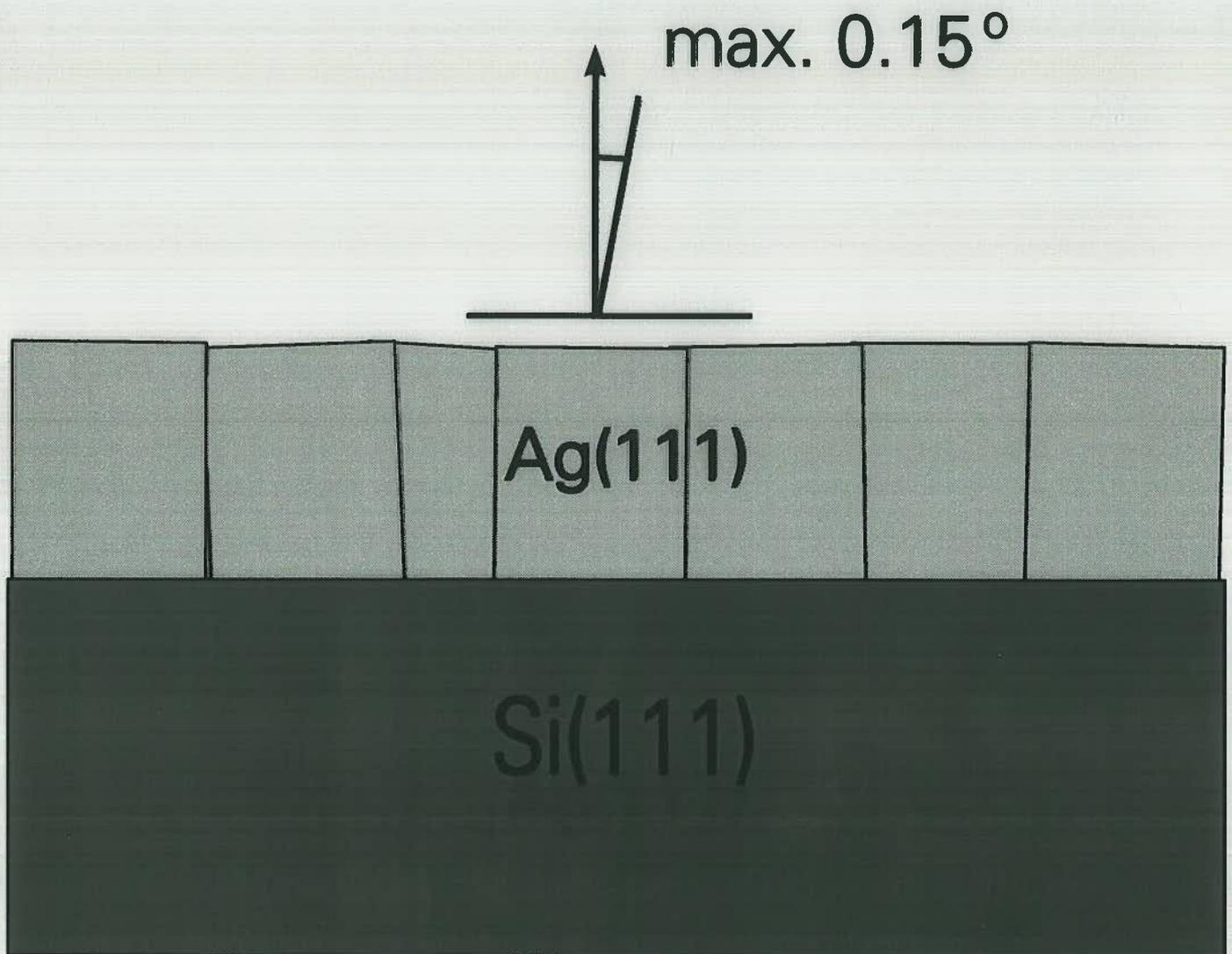
ContScan	View3d	Contour			Drive a:		Mouse
Opti	Mode	Options	Colors	log	HardCopy	Volt	16:43:11
Scan	Scale	Cursor	Rescale	Store a:	Load a:	SControl	10-Scan

100 ML Ag / Si (111)

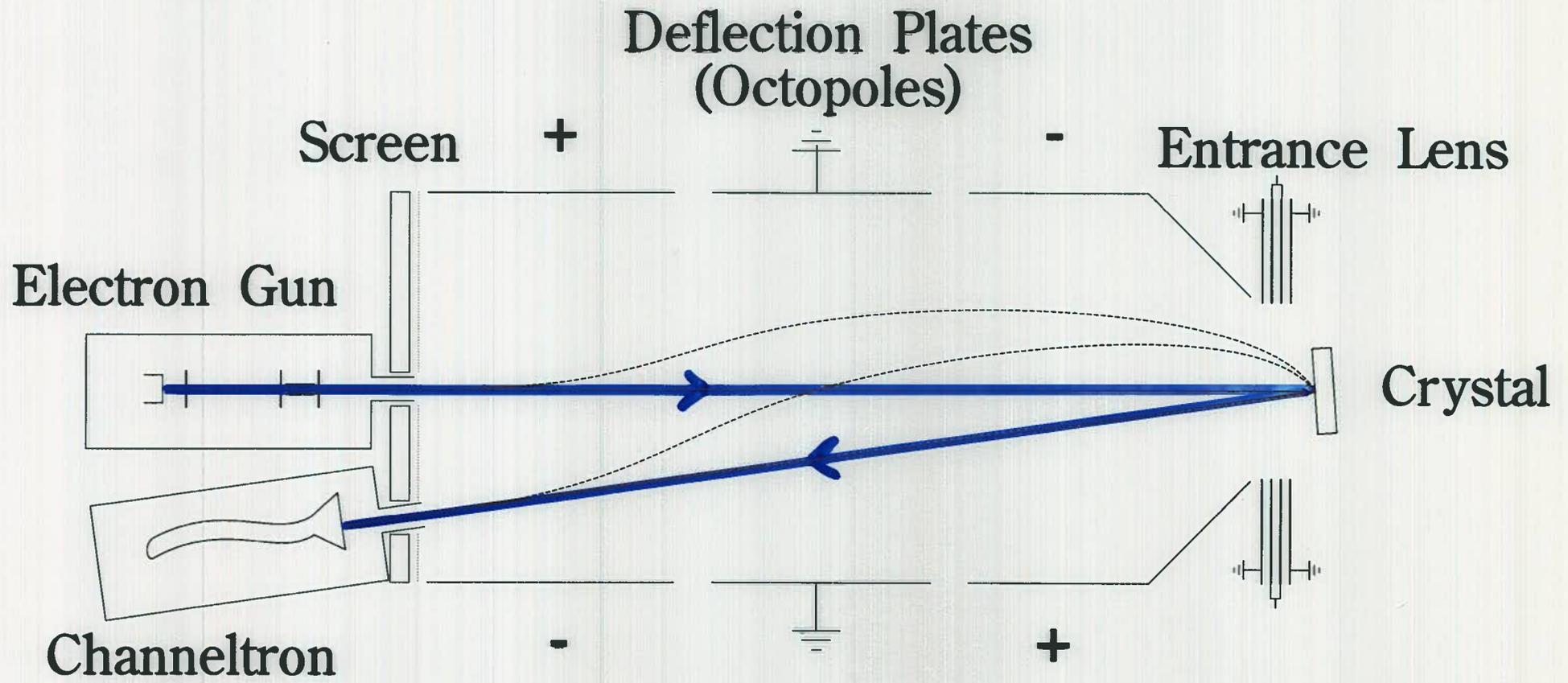
90 K / 500 K



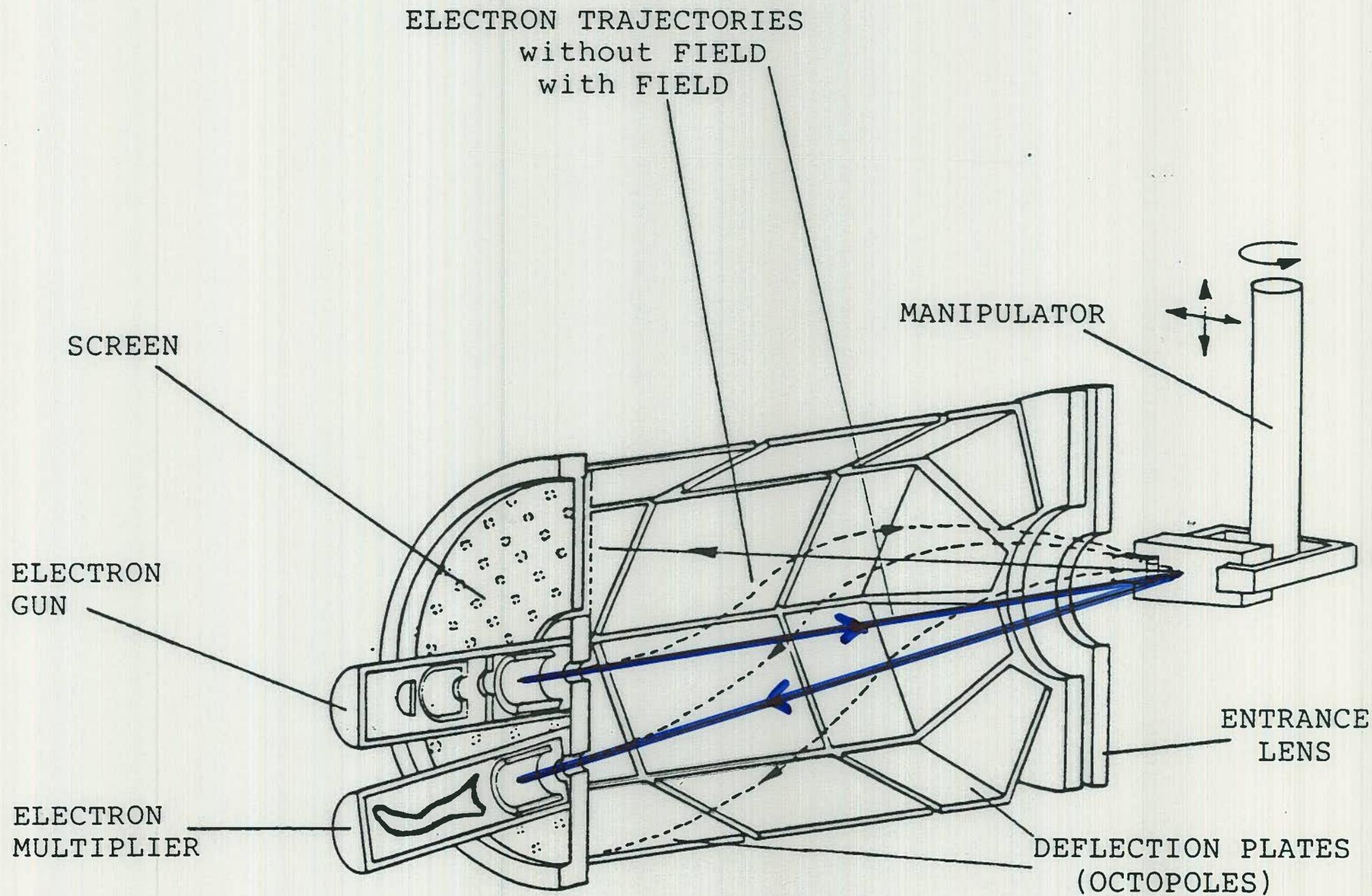
At room temperature silver forms continuous, flat, epitaxial films with small mosaic spread (max. 0.15°) due to steps on the Si(111) substrate



SPA-LEED-Optics



SPA-LEED Optics



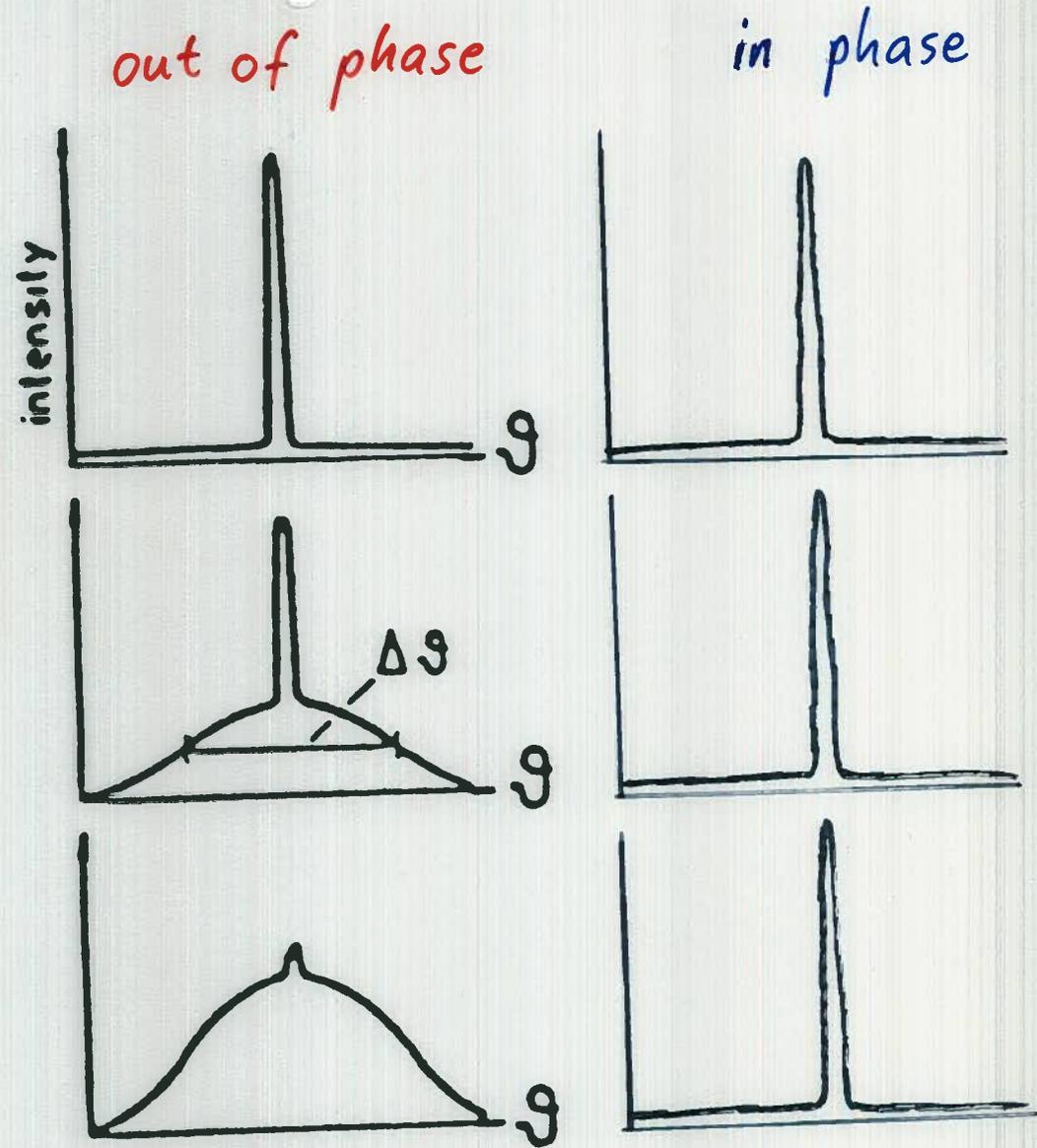
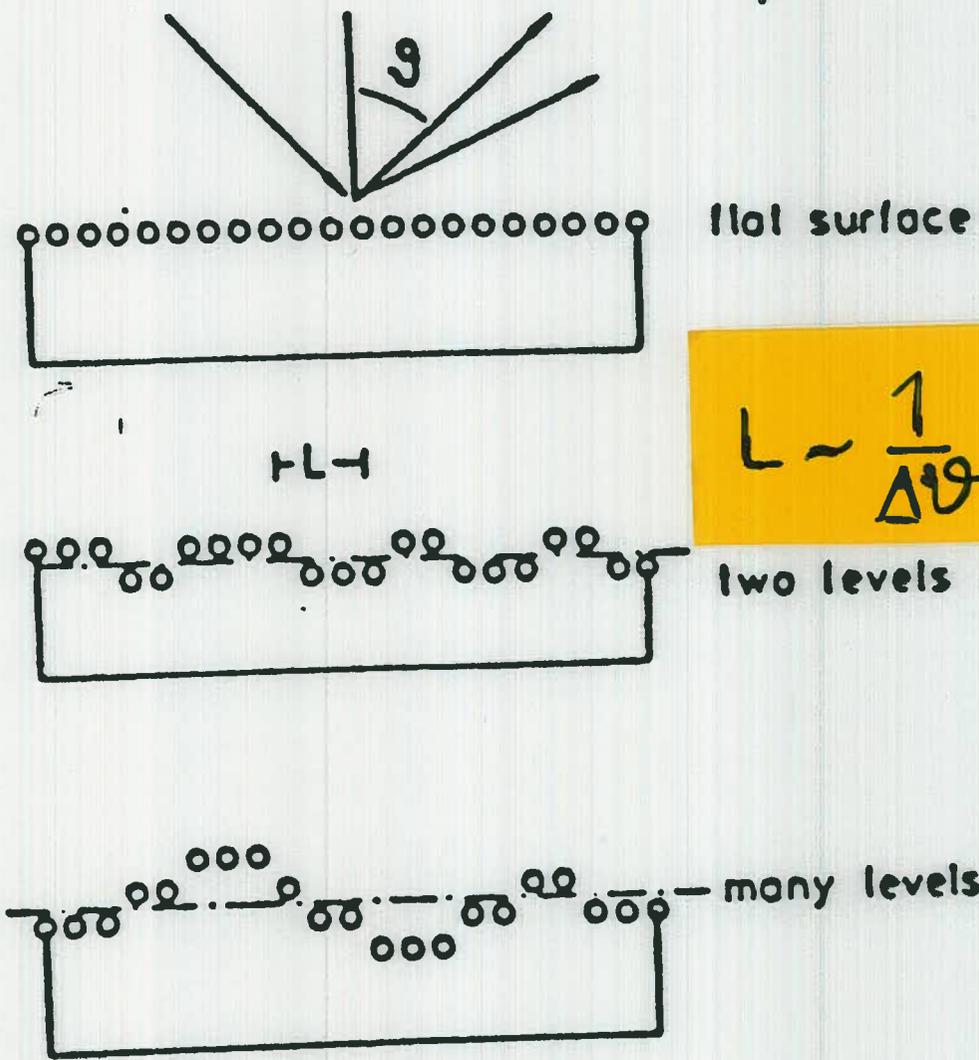
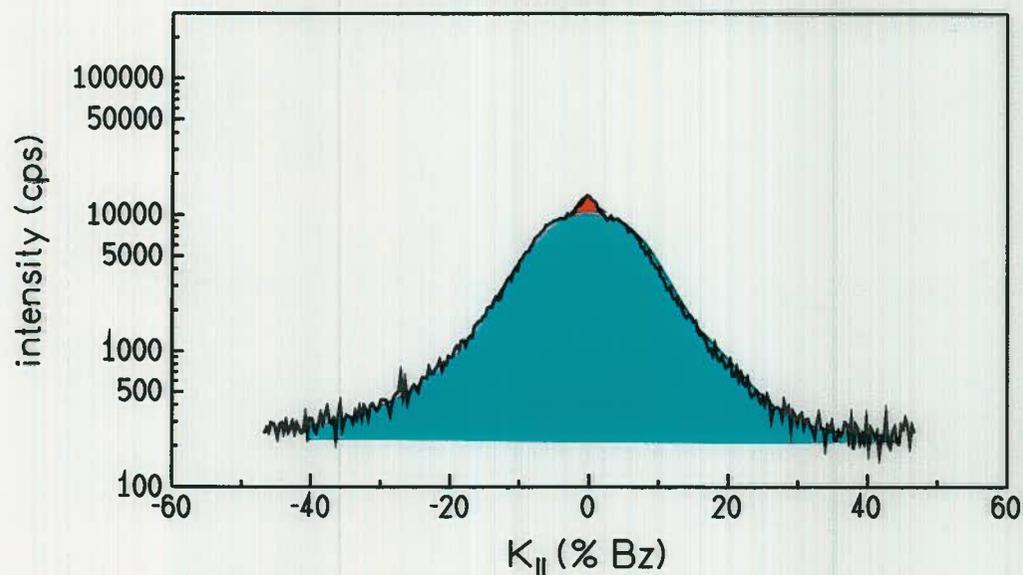


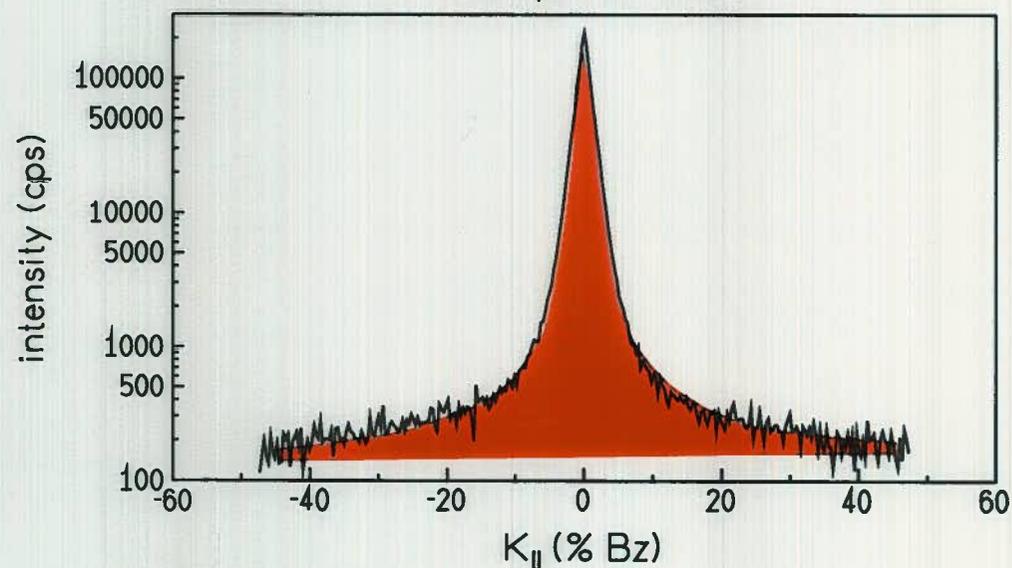
Fig. 1: Observed spot profile (central spike and shoulder for a flat and stepped surface within two and with many levels)

determination of surface roughness

2.5 ML Ag on Ag(111) at 130K
(00)-spot, S = 2.5

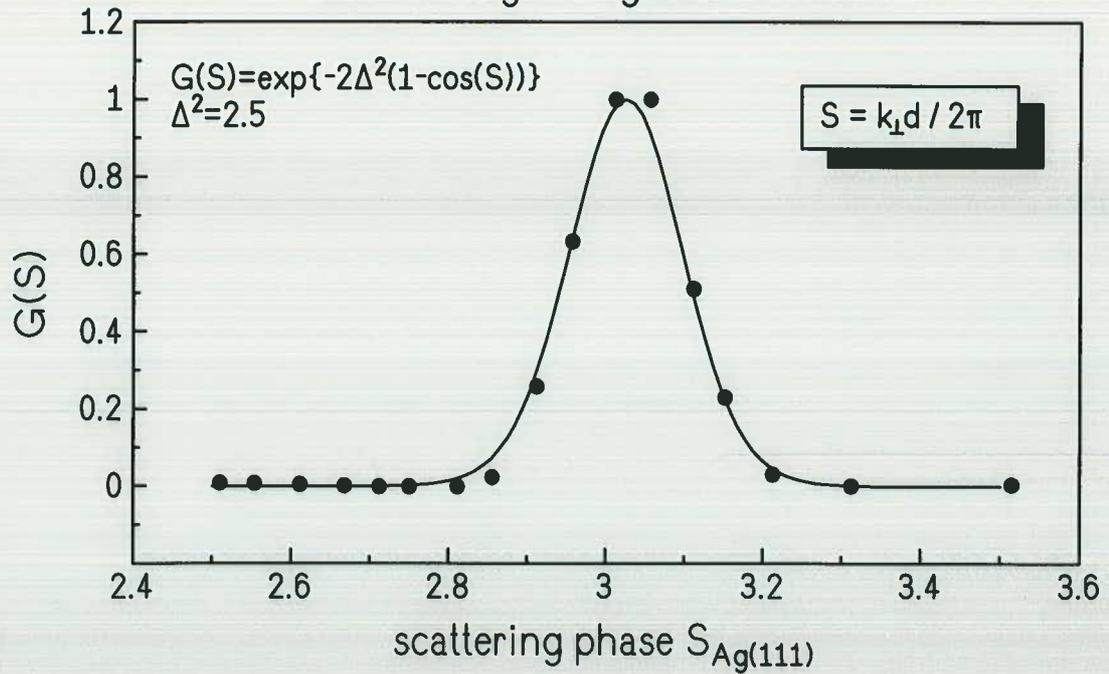


2.5 ML Ag on Ag(111) at 130K
(00)-spot, S = 3.0

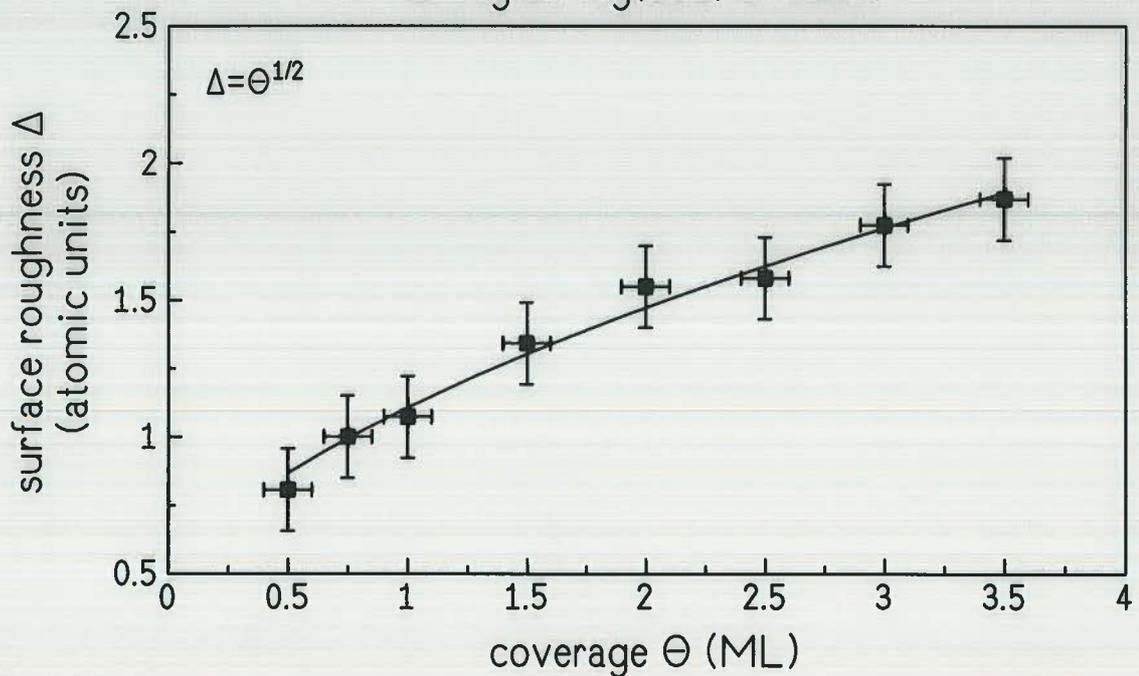


$$G(S) = \frac{I_{\text{Peak}}}{I_{\text{Peak}} + I_{\text{Shoulder}}}$$

2.5 ML Ag on Ag(111) at 130K

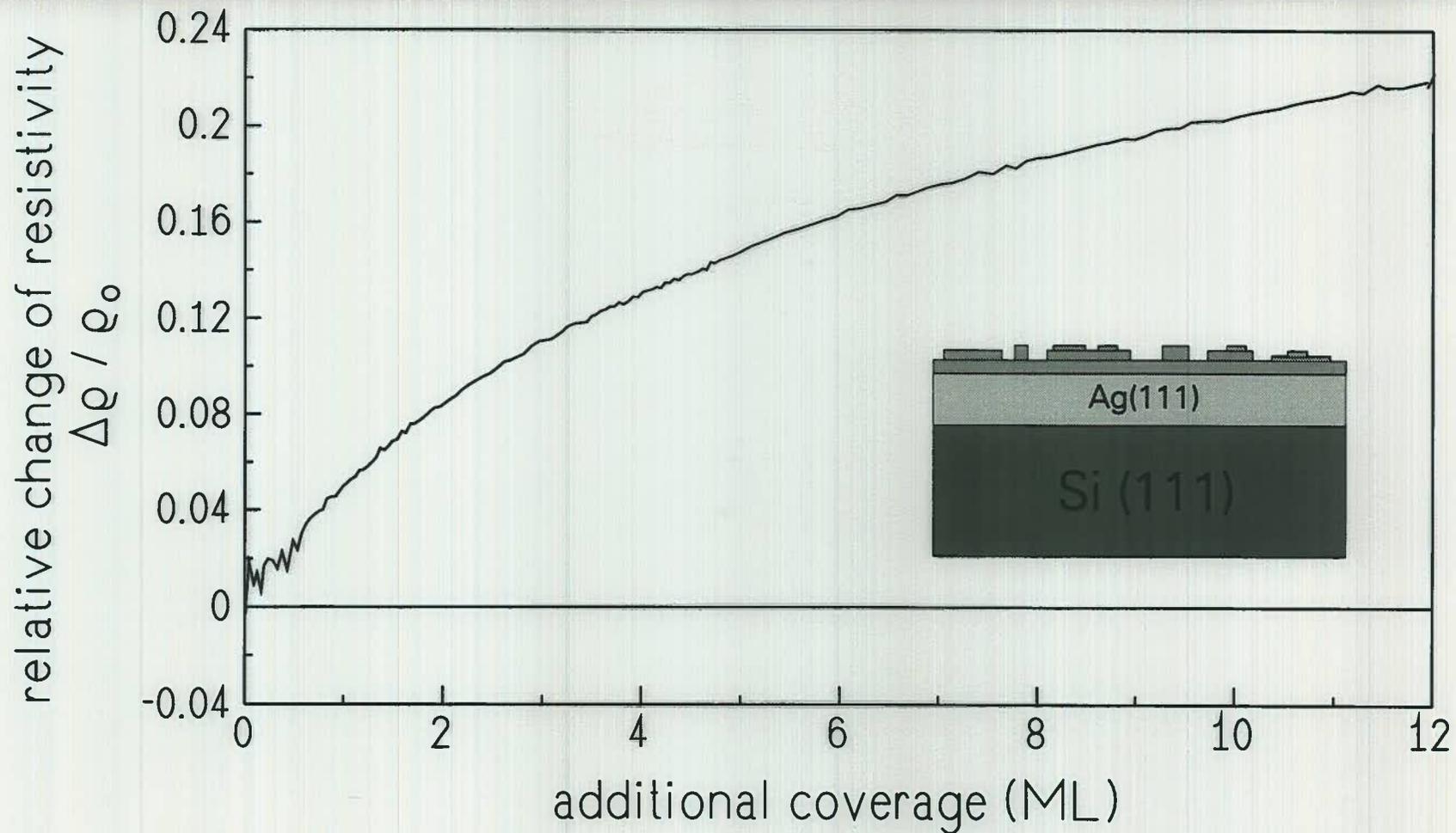


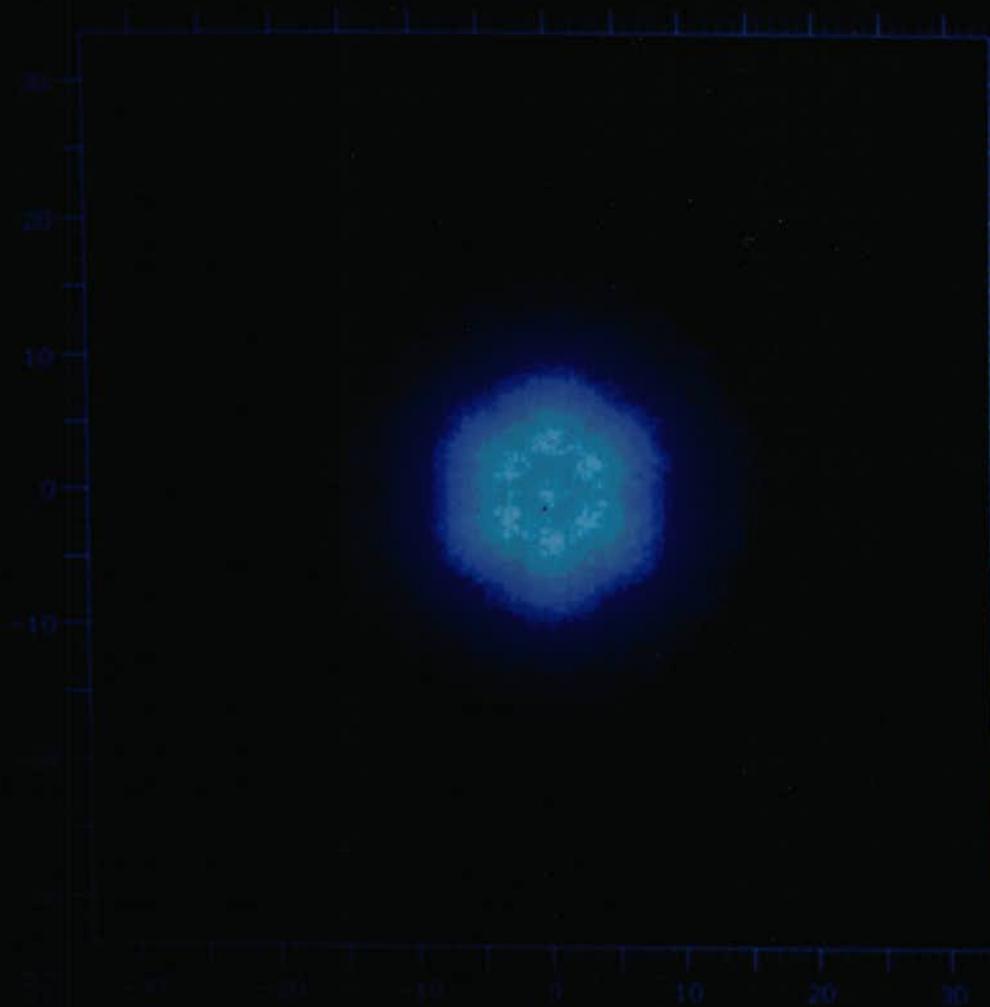
surface roughness Δ during growth of Ag on Ag(111) at 130K



--> statistical growth at 130K

increase of resistivity due to surface roughness scattering by additional deposition of Ag on Ag(111) at low temperature (130K)





```

0001  14.01.97
Xn      0.00      1000
Yn      0.00      1332
Length  20.00      > 1775
Alpha   8.40      > 2366
Points  256      > 3152
Batetime 30.00      > 4200
CpsHigh 29500.0
CpsLow  1000.0
Energy   42.5      > 7404
Current  -17.137   > 8834
TotalTime 0:33 h   > 13237
1.5ML Ag/130K     > 17637
auf 100ML Ag      > 23500
  
```

[F1] Read
 [F2] Code
 [F3]

[F4] Camera
 [F5] Camera
 [F6]

[F7] Colors
 [F8] Rescale

[F9] Log
 [F10] Time w

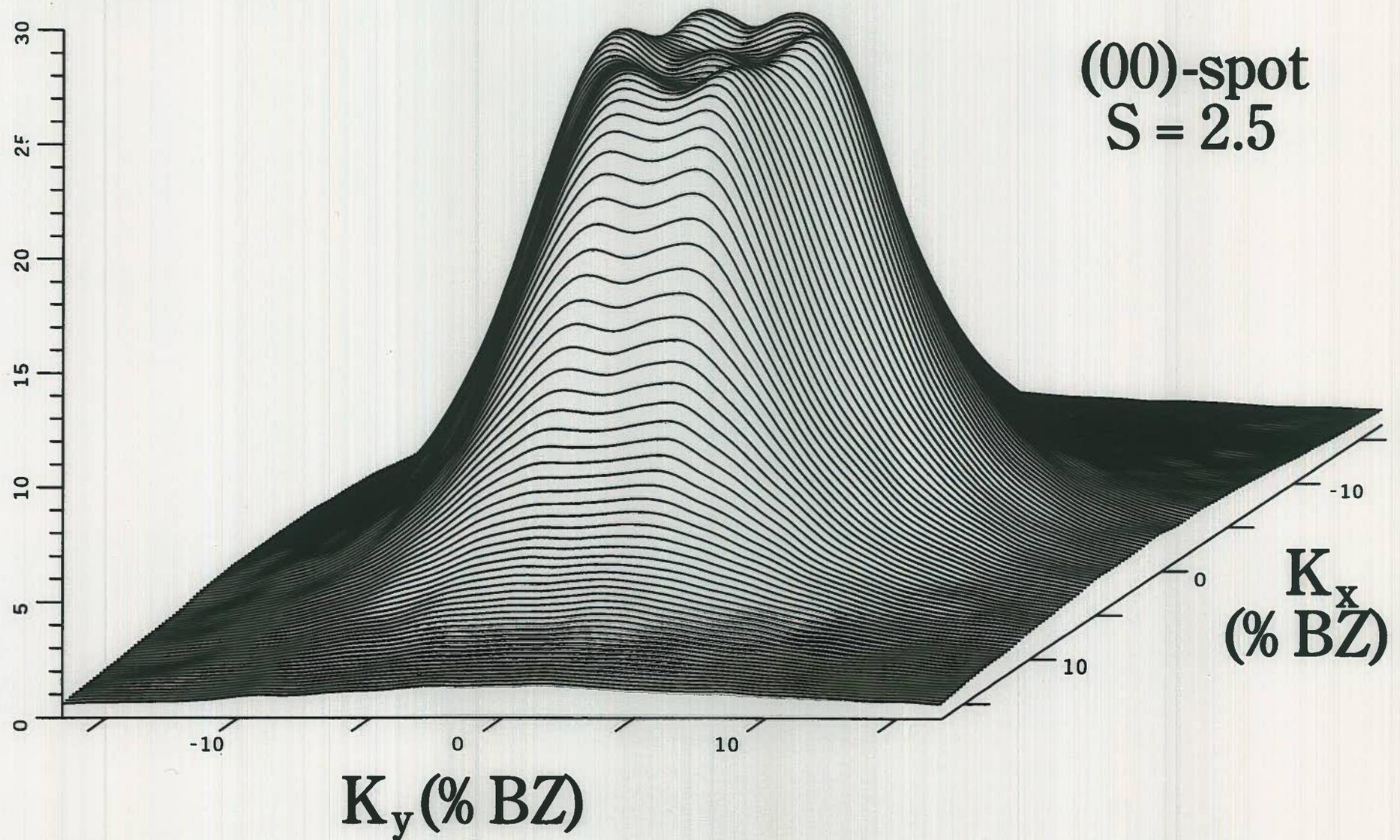
[F11] Drive at
 [F12] Hard Stop
 [F13] Load w

[F14] * trace
 [F15] Control

[F16] House
 [F17] 14.01.97
 [F18] 10:00

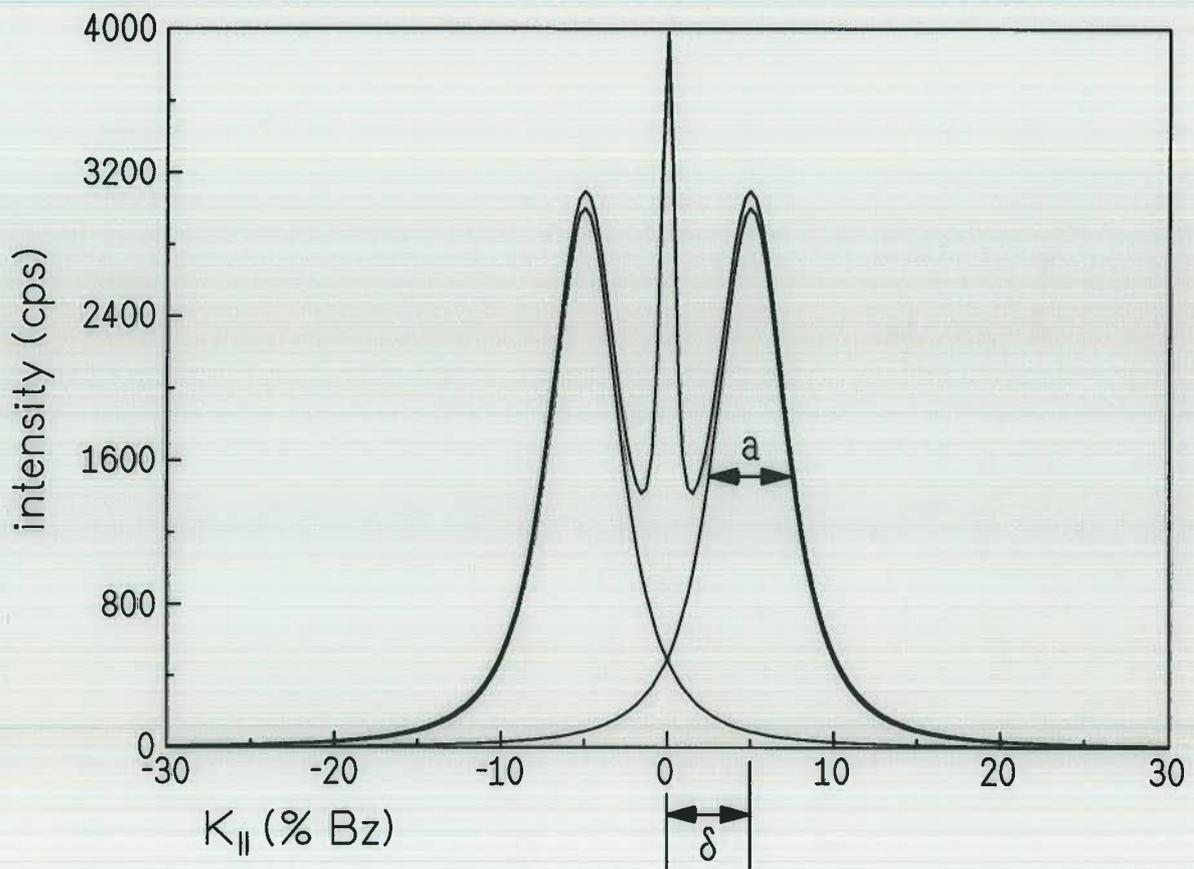
1.5 ML Ag on Ag(111) at 130K

intensity (10^3 cps)



Wollschläger's model

for a stepped surface and
for the out-of-phase condition:

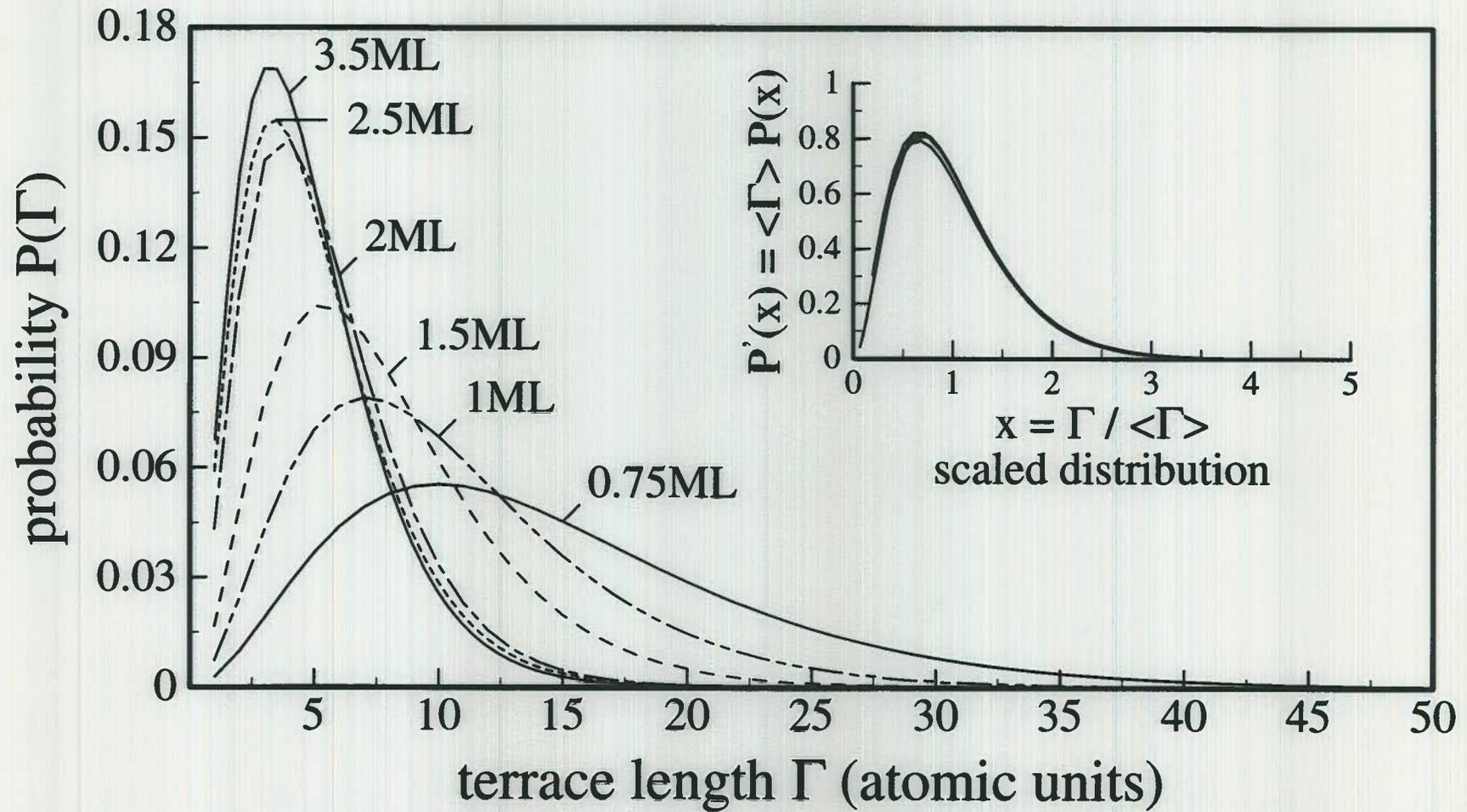


from a, δ follows

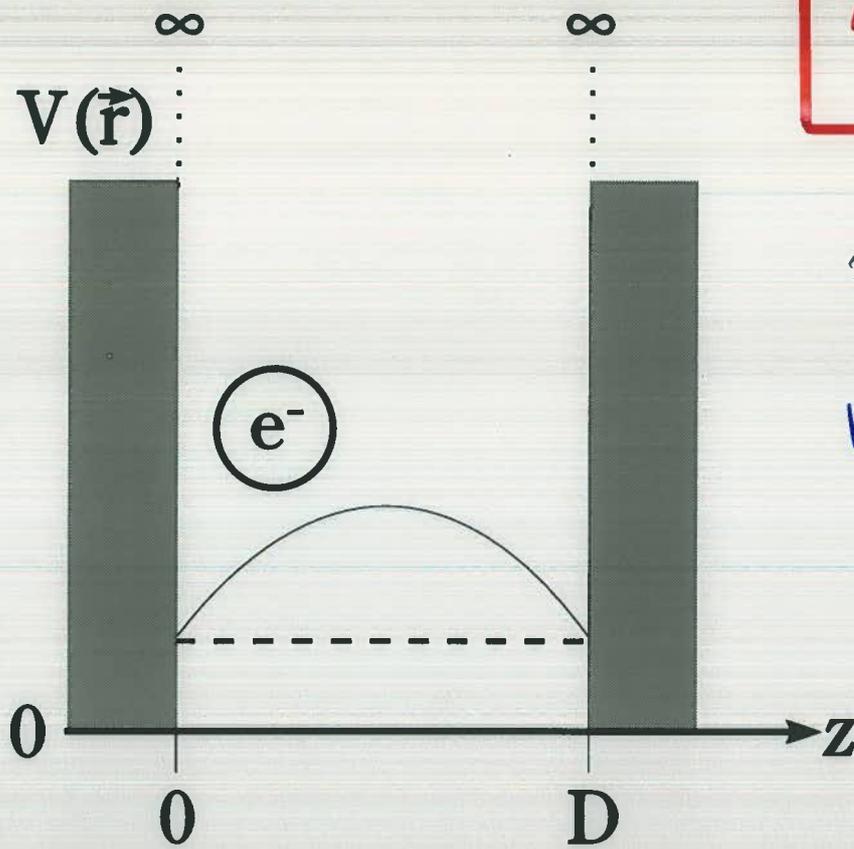
Γ (average terrace length)

σ (standard deviation of Γ)

terrace length distribution for different coverages
Ag on Ag(111) at 130K

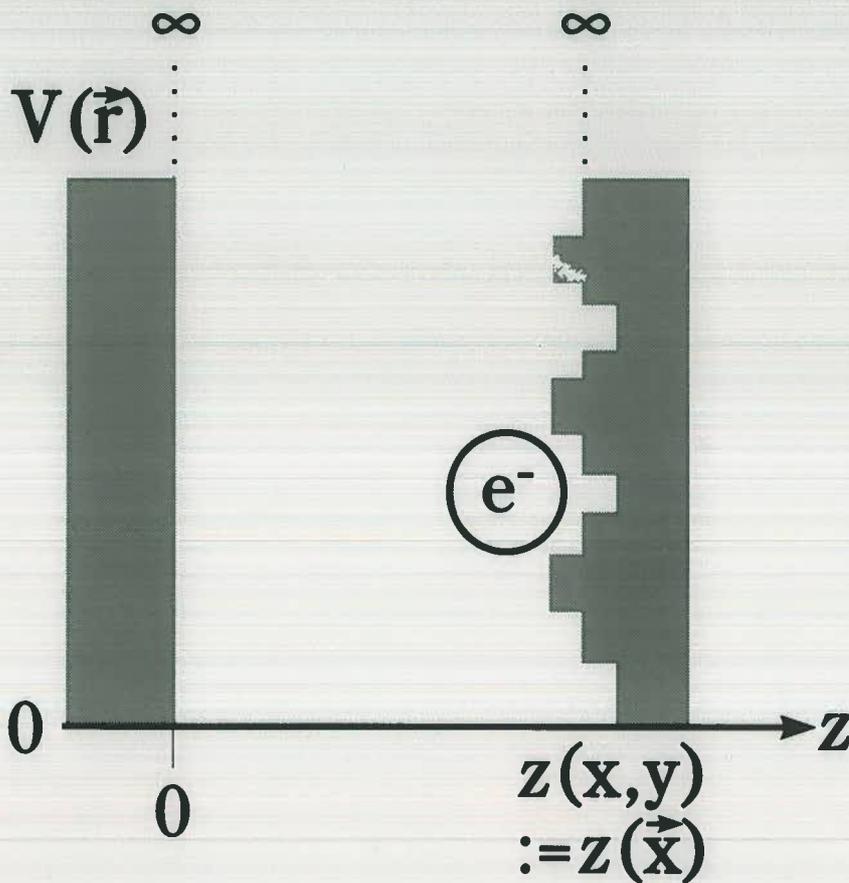


Teilchen im Kasten



Potential

$$V_0(\vec{r}) = \begin{cases} 0 & \text{für } 0 \leq z \leq D \\ \infty & \text{sonst} \end{cases}$$



Potential

$$V(\vec{r}) = V_0(\vec{r}) + V'z(\vec{x})$$

$$\rightarrow H = H_0 + H'$$

$$\text{mit } H_0 = -\frac{\hbar^2}{2m} \nabla^2 + V_0(\vec{r})$$

$$\text{und } H' = V'z(\vec{x})$$

Modell freier Elektronen:

$$\langle \vec{x} | \vec{k} \rangle \propto e^{i\vec{k} \cdot \vec{x}}$$

Übergangsmatrixelement:

$$M_{\vec{k}, \vec{k}'} \propto \langle \vec{k} | H' | \vec{k}' \rangle$$

$$\propto V' \int d^2x \tau(\vec{x}) e^{i(\vec{k} - \vec{k}') \cdot \vec{x}}$$

Verweildauer im Zustand $|\vec{k}\rangle$:

$$\tau_{\vec{k}, \vec{k}'}^{-1} \propto |\langle \vec{k} | H' | \vec{k}' \rangle|^2$$

$$\propto |V'|^2 \int d^2x f(\vec{x}) e^{i\vec{Q} \cdot \vec{x}}$$

$$\text{mit } \vec{Q} = \vec{k} - \vec{k}'$$

$$\text{und } f(\vec{x}) = \int d^2x' \tau(\vec{x}') \tau(\vec{x}' + \vec{x})$$
$$:= \Delta^2 \exp\{-x/\xi\}$$

integriere über Fermikugel $\rightarrow \tau^{-1}$

$$\rho \propto \tau^{-1} = (\Delta\xi)^2 F(\xi)$$

Theoretische Ansätze

① Fuchs / Sondheimer

② Leung

Gerlach / Kaser

$$\Delta g \propto \Delta^2 \xi^2 F(k_F \xi) \xrightarrow{k_F \xi \gg 1} \Delta^2 / \xi$$

mit Korrelationslänge ξ aus Autokorrelation

$$A(\rho) = \langle H(\rho + \rho') H(\rho') \rangle =: \Delta^2 e^{-\rho/\xi}$$

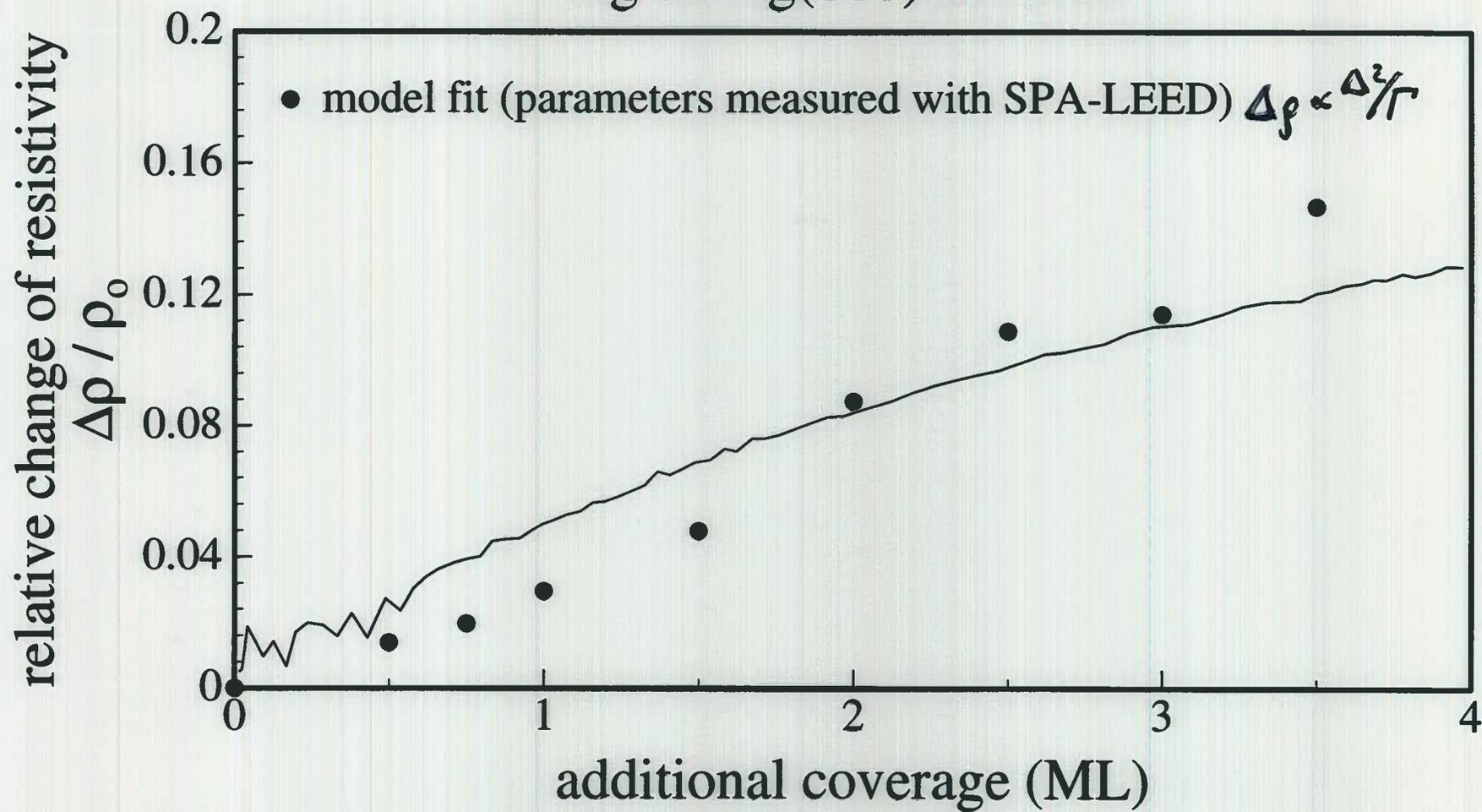
③ Wiparman: Springer Tracts Mod. Phys. 77 (1975) 1

$$\Delta g \propto \Omega \cdot n_{\text{Streuer}} \propto 1/r$$

↑
Streuzerschnitt

$$\Gamma = \xi / 4 \Delta^2 \xrightarrow{\text{②}} \Delta g \propto 1/r$$

comparison between measurement and theory
Ag on Ag(111) at 130K



Beitrag zur allgemeinen Begriffsverwirrung
(Dr. J. Wollschläger)

Autokorrelation $a(p) = \langle H(p+p') H(p') \rangle =: \Delta^2 e^{-p/\xi}$
 $= \mathcal{F} \{ |\mathcal{F} \{ H(p) \}|^2 \} \rightarrow \xi$

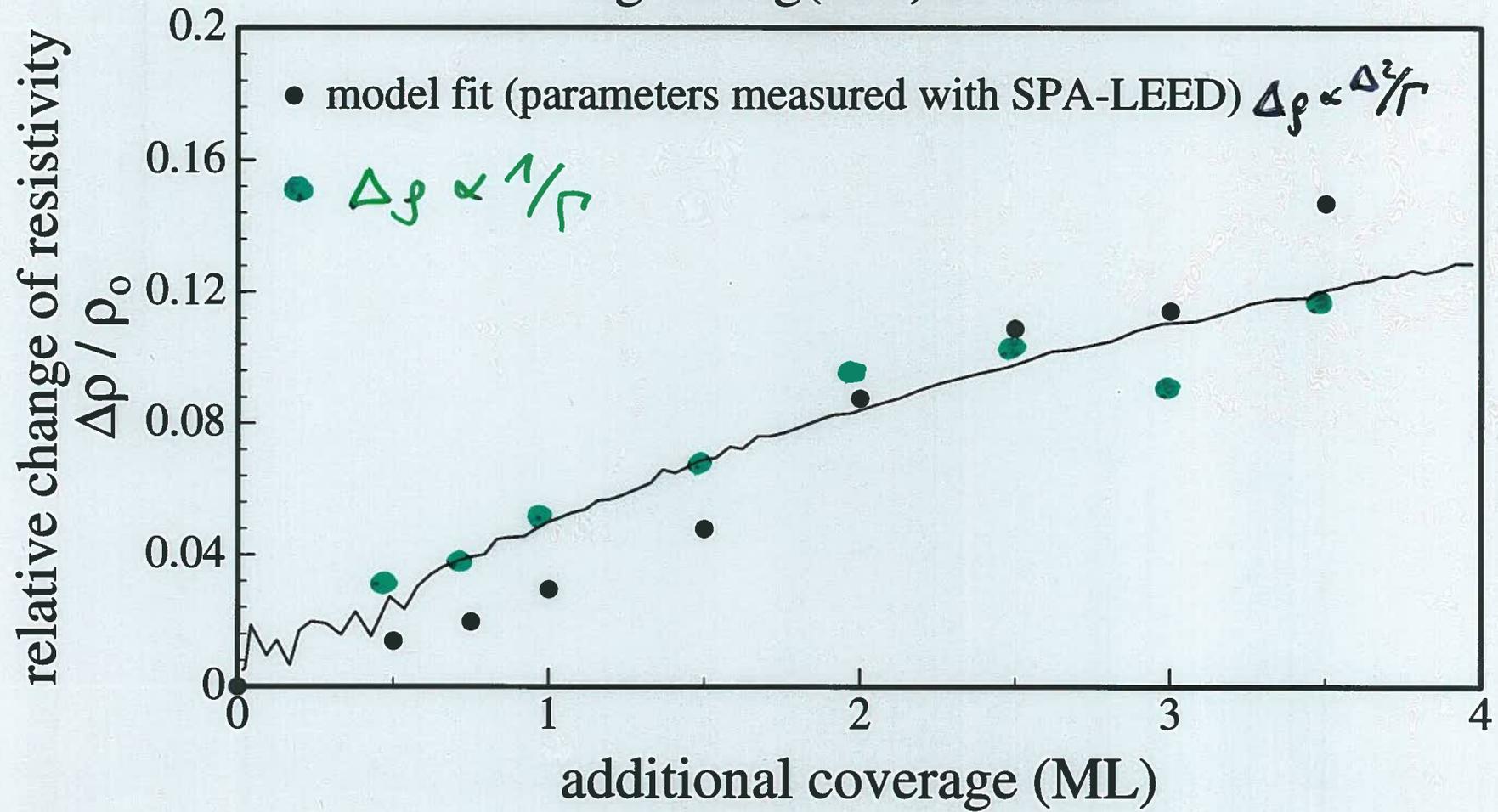
Phasenkorrelation $\phi(p, S) = \langle e^{2\pi i \cdot S [H(p+p') - H(p)]} \rangle$
(SPA-LEED) $\rightarrow \Gamma$



2

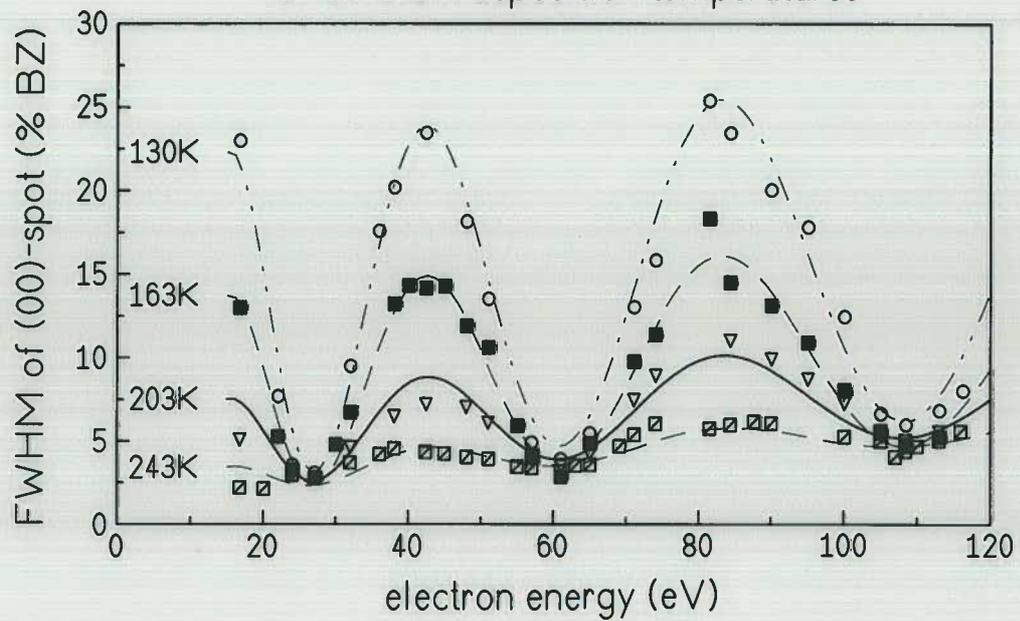
$$\Gamma = \xi / 4\Delta^2$$

comparison between measurement and theory
Ag on Ag(111) at 130K

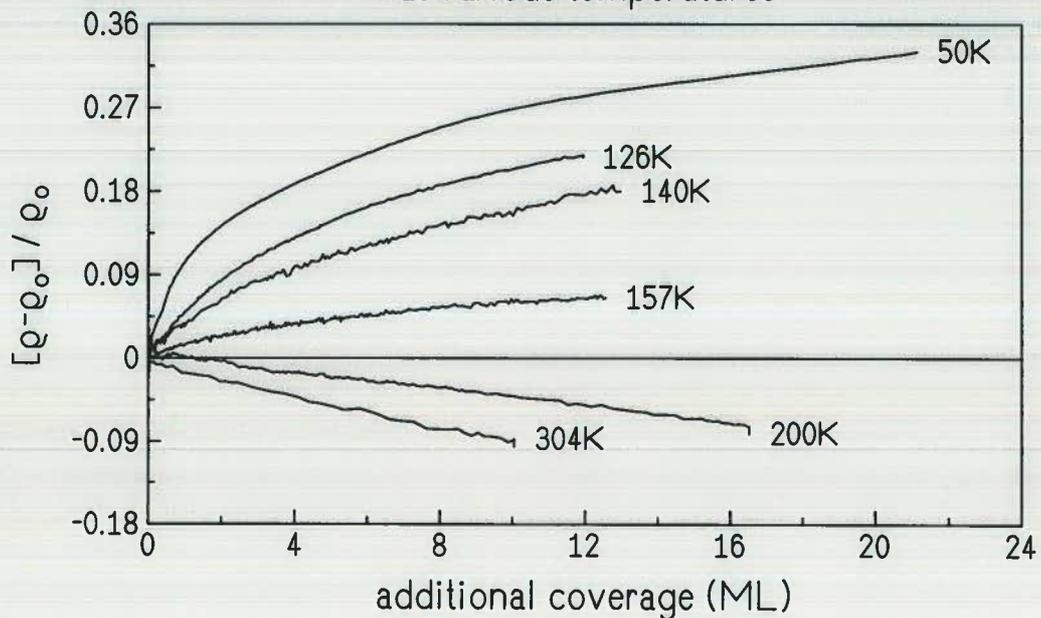


influence of deposition temperature

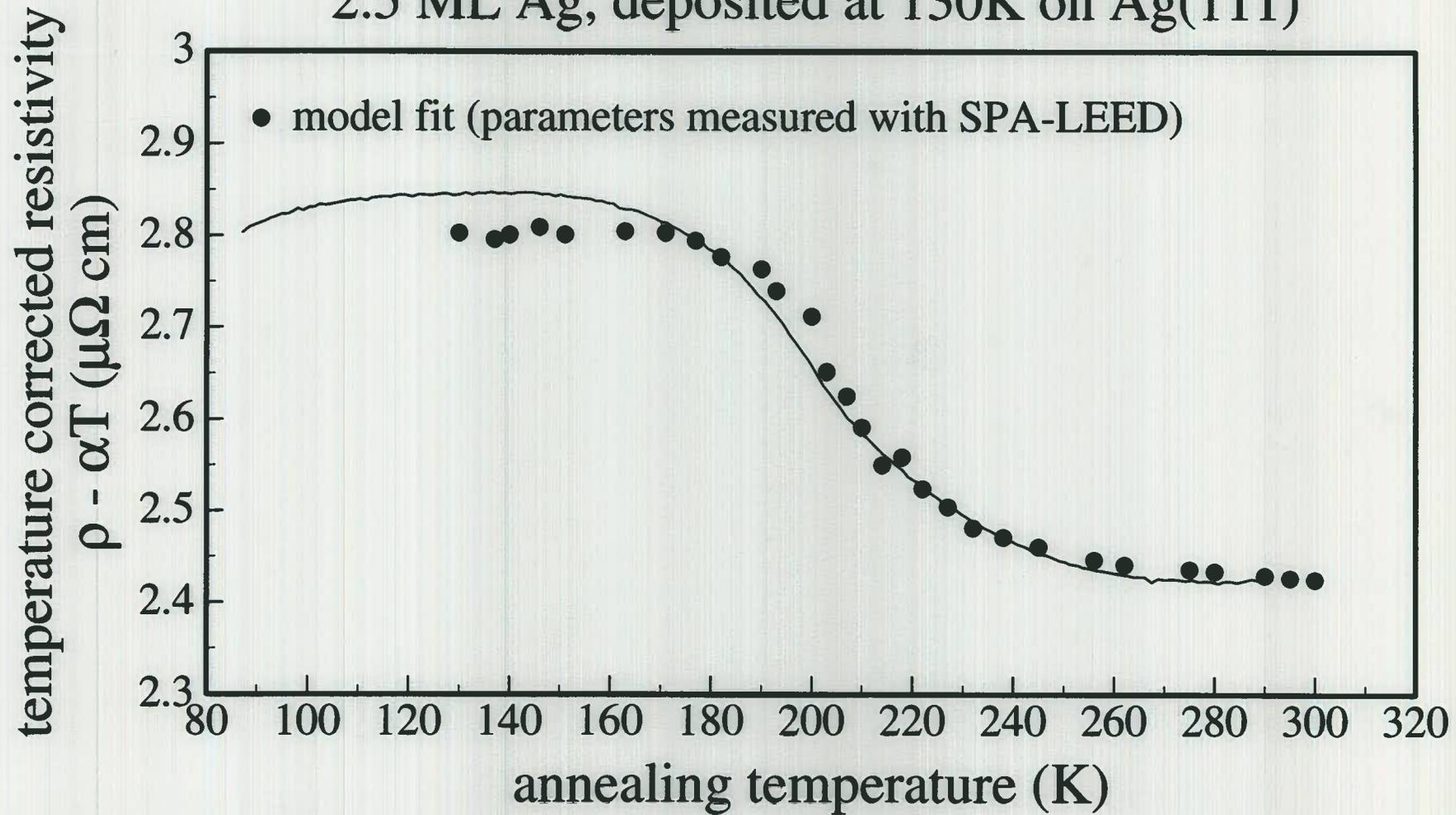
2 ML Ag / Ag(111)
for different deposition temperatures



resistivity change during deposition of Ag on Ag(111)
at various temperatures



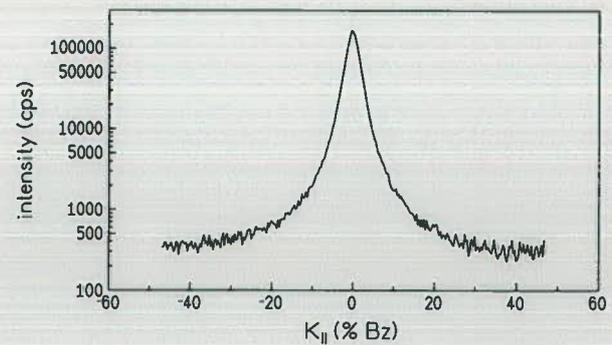
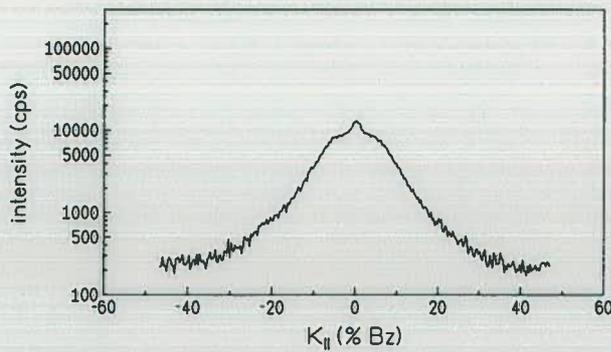
comparison between measurement and theory
2.5 ML Ag, deposited at 130K on Ag(111)



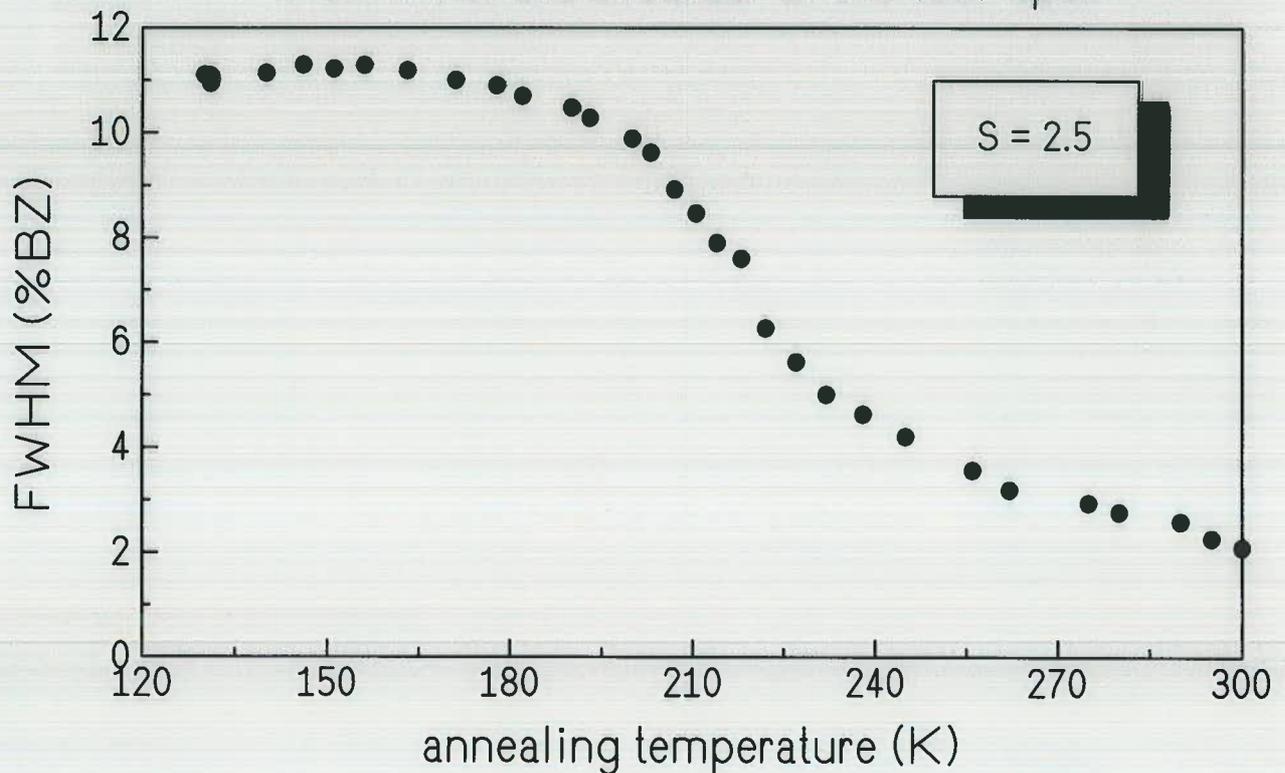
annealing experiment

2.5 ML Ag on Ag(111)

as deposited at 130K after annealing to 260K

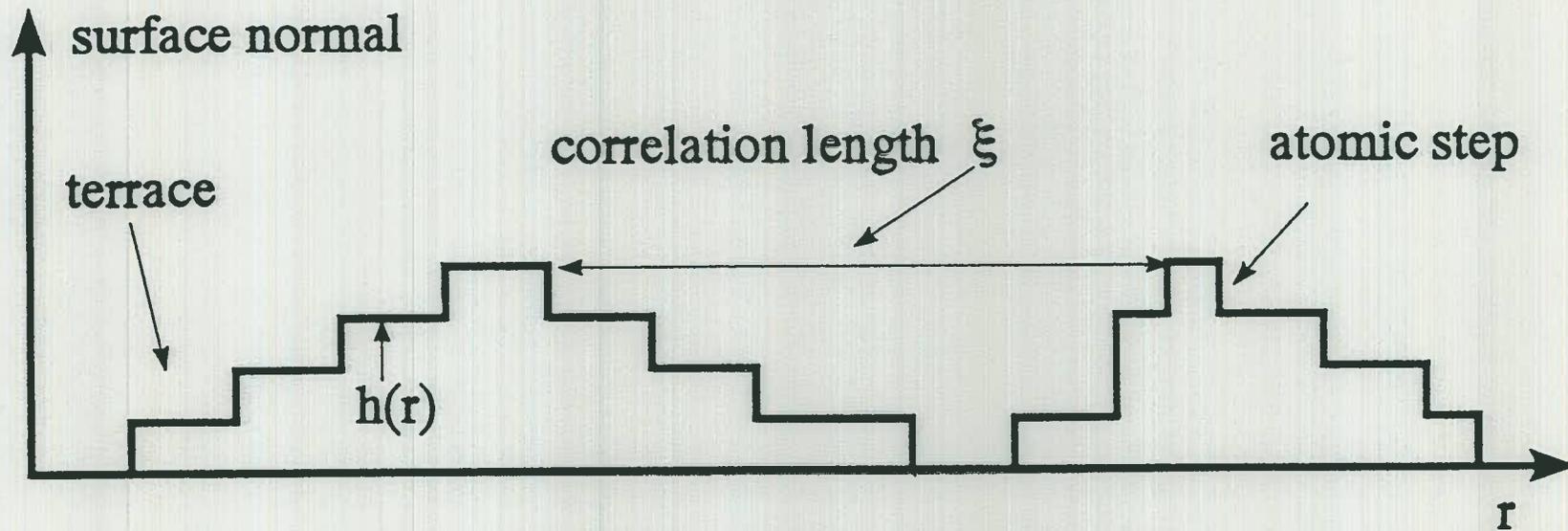


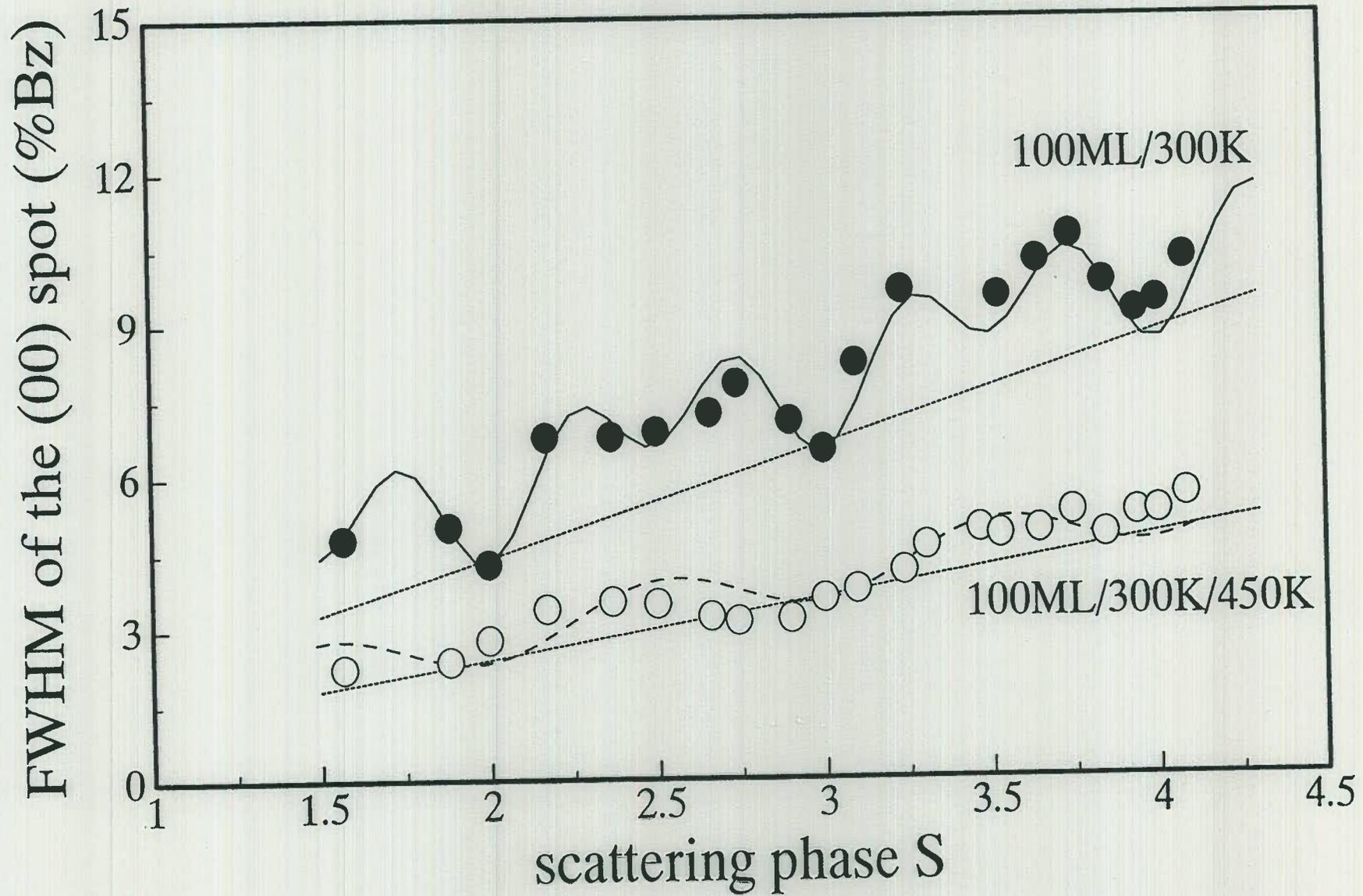
FWHM of the shoulder of the (00)-spot

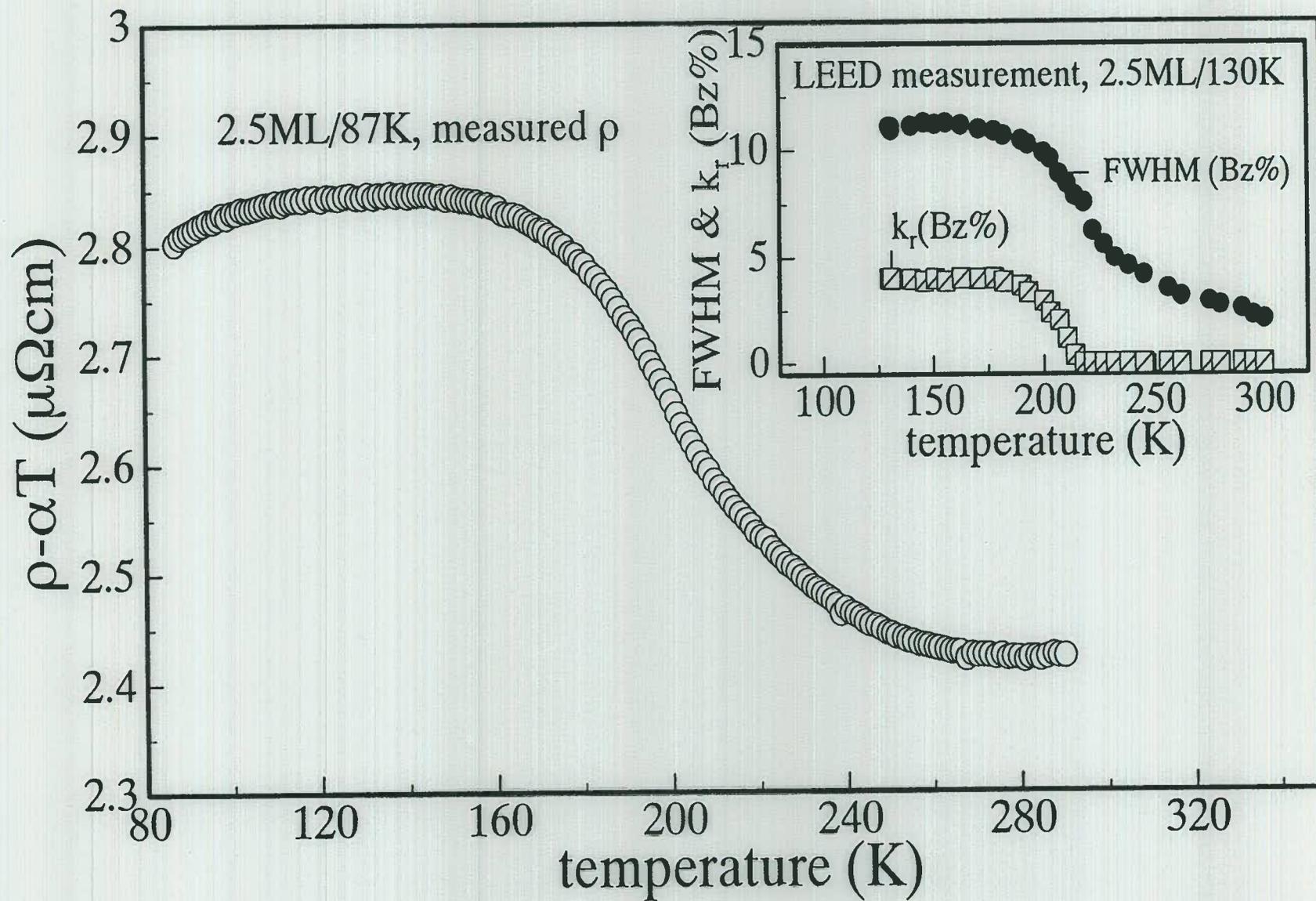


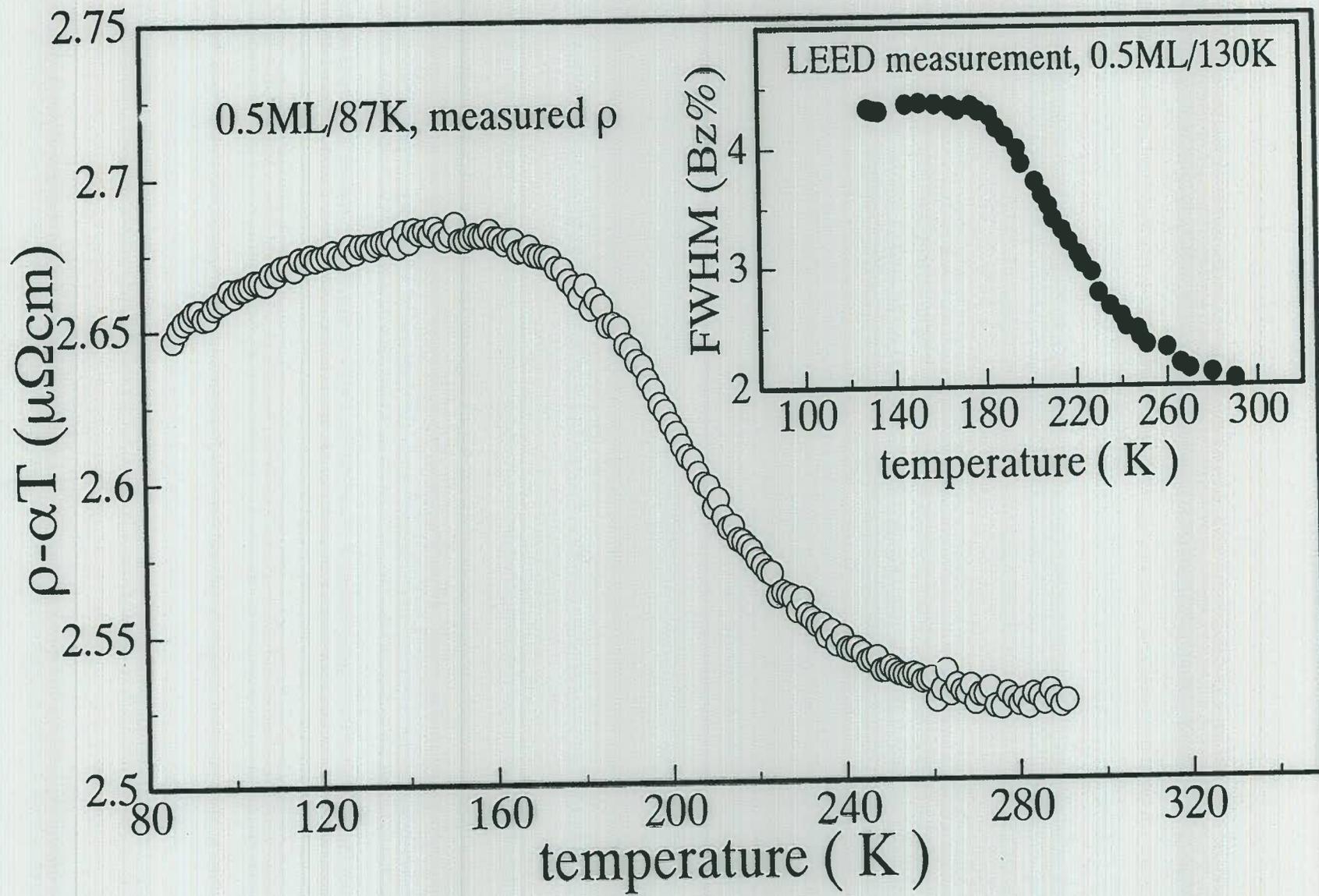
1. measuring surface morphology.
SPA-LEED yields statistical informations like
 - . surface roughness Δ
 - . terrace length distribution Γ, σ
2. measurement of the corresponding change in resistivity ρ
3. comparison of both results, using the the **measured** structural data to explain resistivity measurements

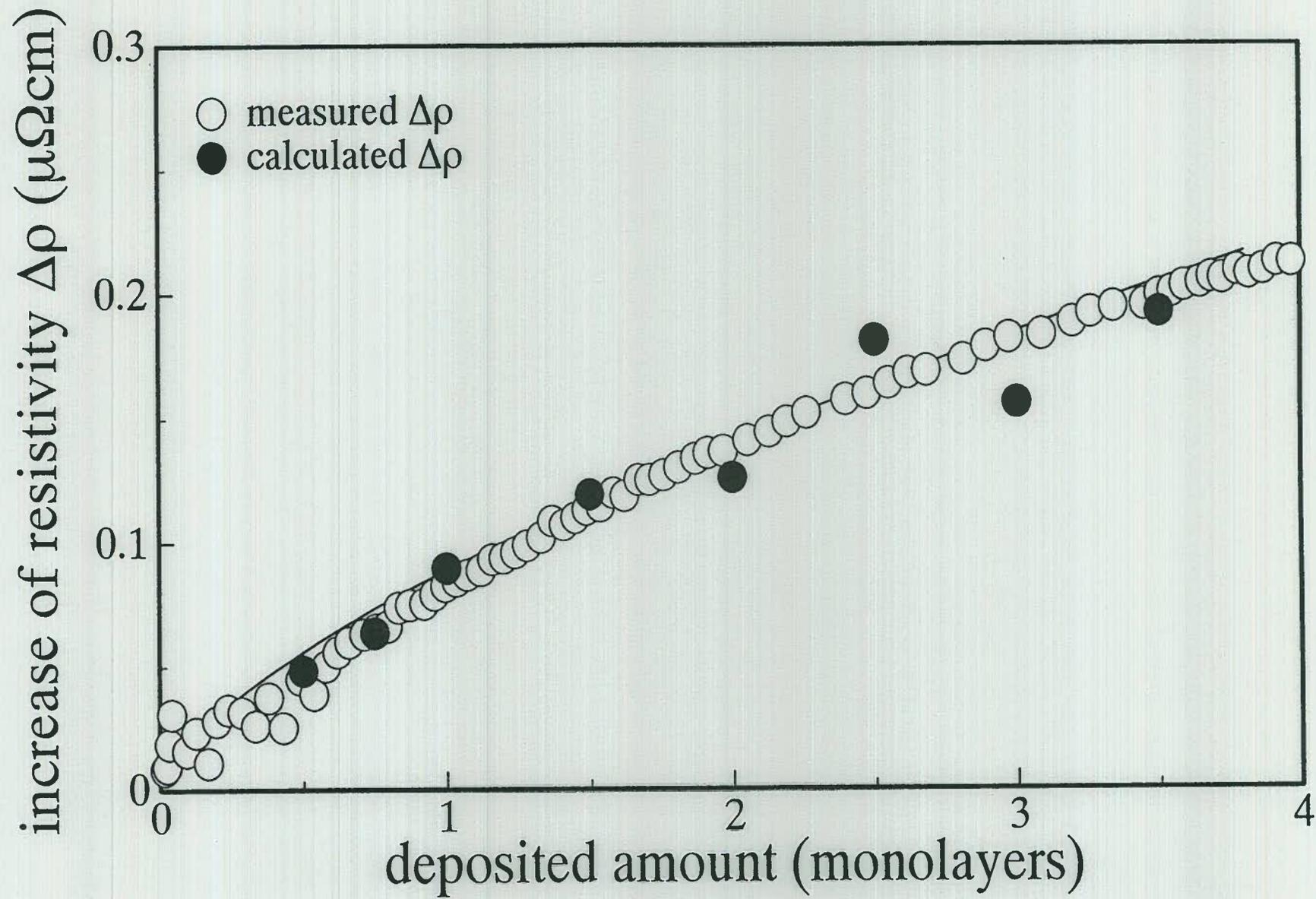
aim: a deeper understanding of electronic scattering processes on interfaces

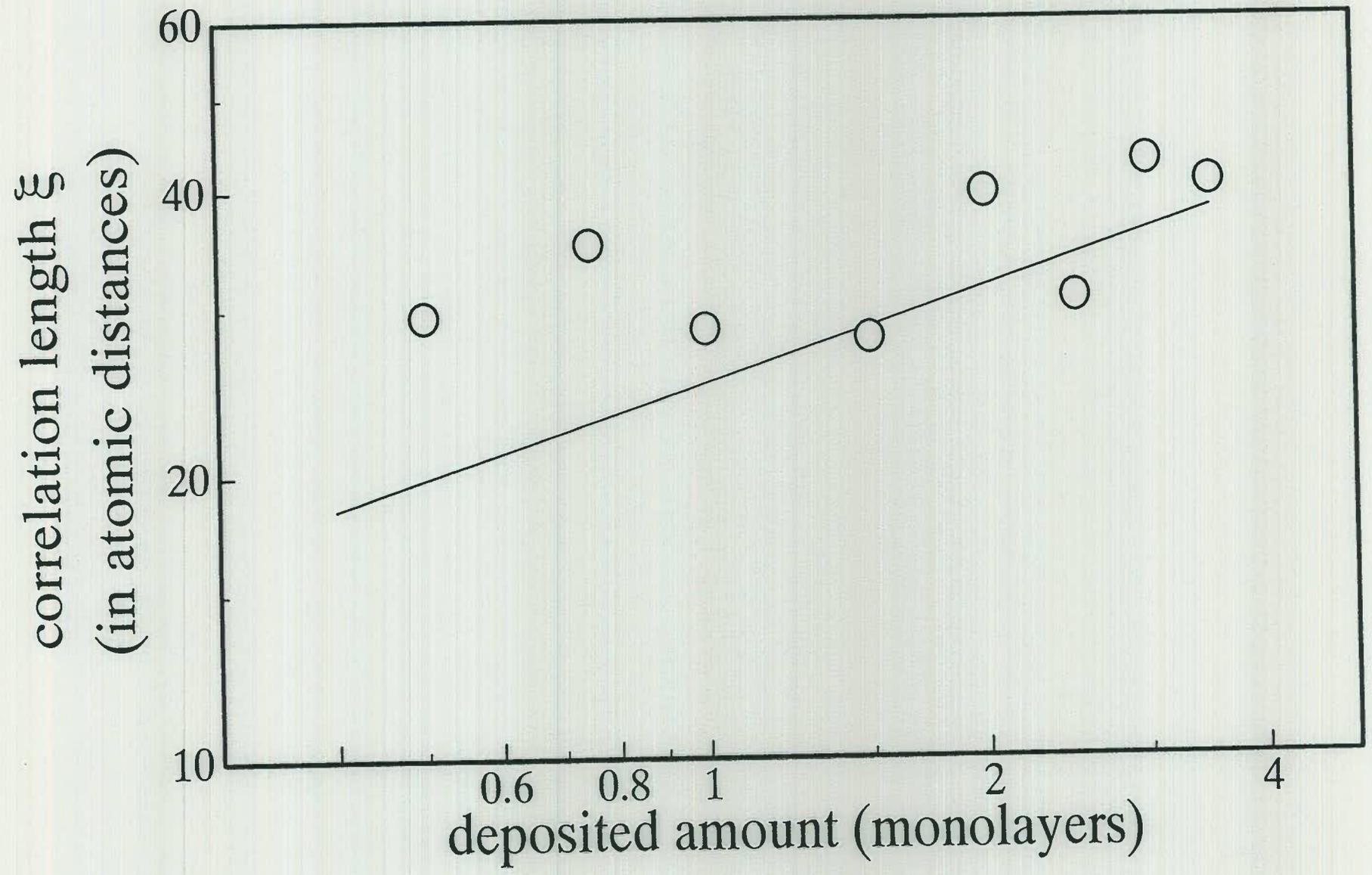


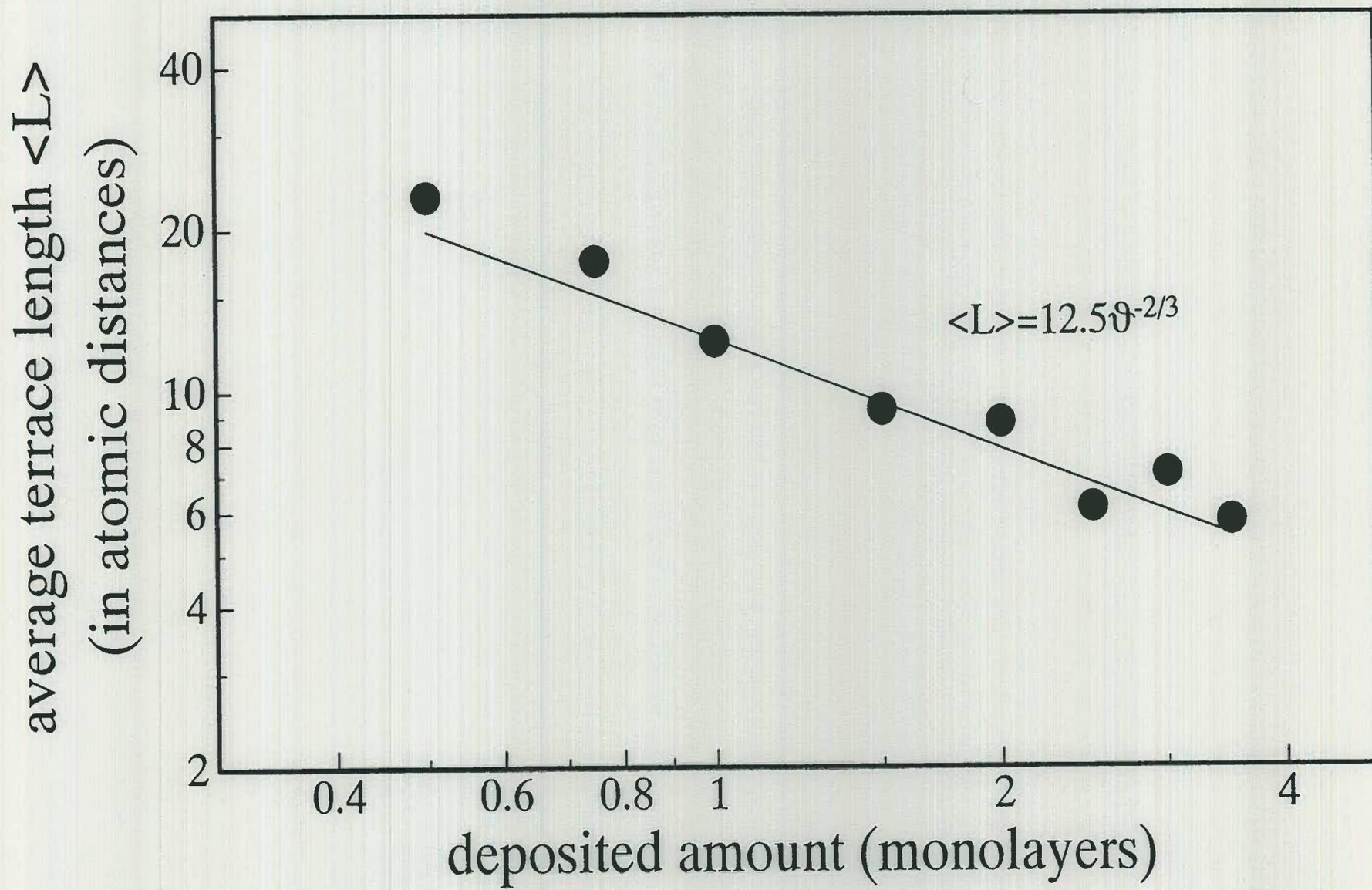


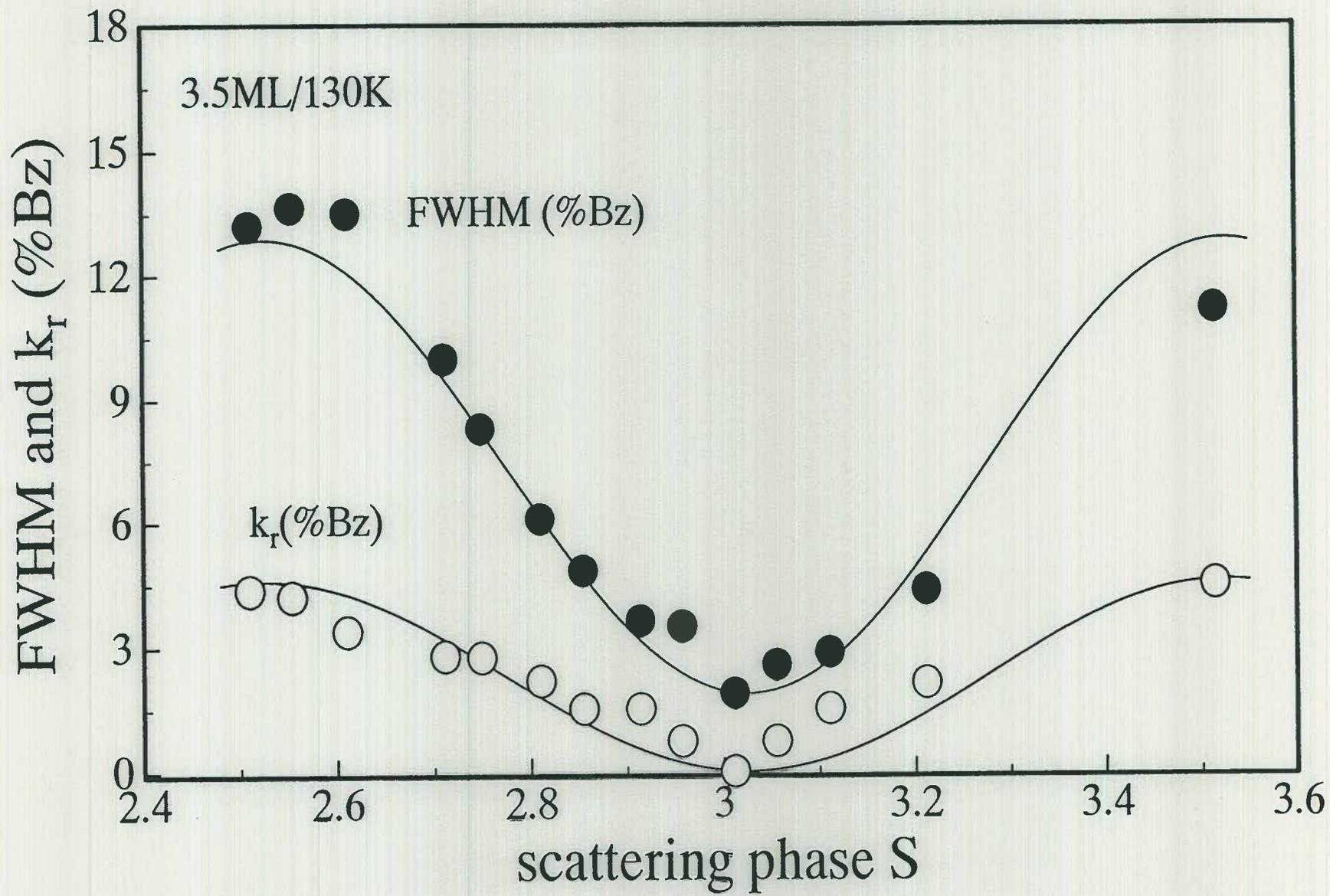


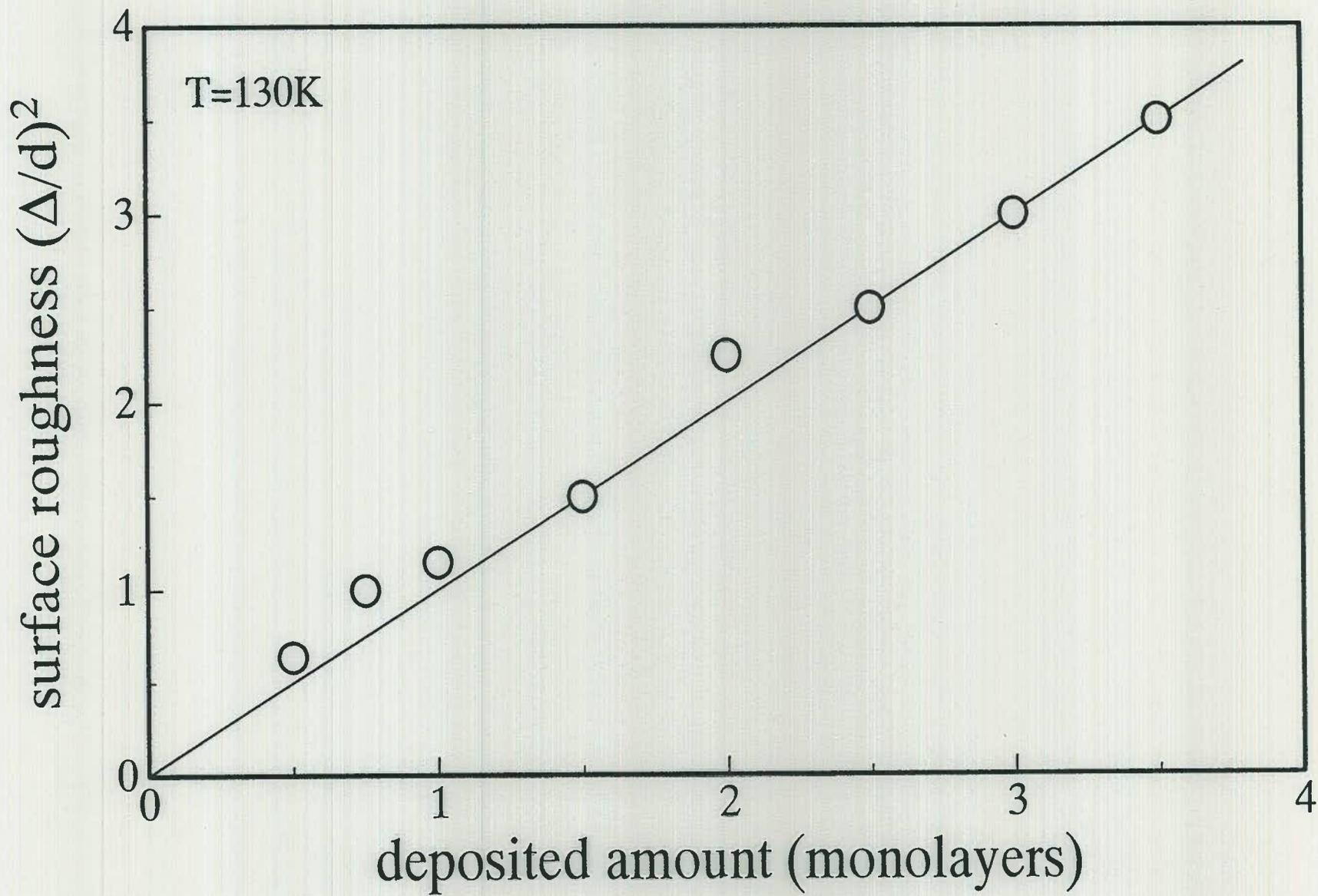












intensity (a.u.)

